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Description

The present invention relates to a method for transferring an embossed structure to a surface of a coating composition (B2a), which comprises the steps (1-i) and (2-i) or (1-ii) and (2-ii) and also the steps (3) and optionally (4), where the steps (1-i) and (2-i) or (1-ii) and (2-ii) are performed using a composite (F1B1) which is employed as embossing die (p2) of an embossing tool (P2) and which is composed of a substrate (F1) and of an at least partially embossed and at least partially cured coating (B1), and the coating composition (B1a) used for producing (B1) of the composite (F1B1) is a radiation-curable coating composition of defined constitution, to a composite (F1B1), and also to a use of the composite (F1B1) as embossing die (p2) of an embossing tool (P2) for transferring an embossed structure to at least a part of a surface of a coating composition (B2a).

Prior art

In many applications within industry it is nowadays customary to provide workpieces on their surface with structures whose structural features are in the micrometer range or even in the nanometer range. Such structures are also referred to as microstructures (structures with features in the micrometer range) or nanostructures (structures with features in the nanometer range). Such structures are used, for example, to influence optical, bionic and/or tactile qualities of materials surfaces. Structures of this kind are also referred to as embossments or embossed structures.

One common method here is to transfer these structures into a coating material. Transfer of the structures into the coating material is frequently achieved here with an embossing operation wherein a die containing, on an embossed surface or transfer surface, the microstructures and/or nanostructures to be formed, in a negative form, is brought into contact with and impressed into the coating material. In order then for the structures to be permanently formed and maintained on the surface of the

workpiece, the coating material is typically cured *in situ*.

WO 90/15673 A1 describes a method wherein a radiation-curable coating material is applied to a film or to an embossed die with the negative desired embossed structure, and the embossing tool is then printed onto the foil, to the foil provided with the coating material or to the embossing tool providing with the coating material. While the radiation-curable coating material is still located between foil and embossing tool, curing is carried out and then, following removal of the tool, a film is obtained which is provided with a radiation-cured coating material that comprises the desired positive feature structure. European patent EP 1 135 267 B1 as well describes a method of this kind wherein a curable coating material is applied to the substrate surface for decoration, and a corresponding embossed die with negative pattern is pressed into the uncured coating layer. Thereafter the coating layer is cured and the embossing die is subsequently removed. EP 3 178 653 A1 discloses an article comprising a flexible fabric having a textured surface for use in the replicative casting of curable systems. The fabric may have polymer layers which can be produced by using mono- and polyfunctional acrylates.

US Patent No. 9,778,564 B2 discloses an imprint material which includes a component which necessarily comprises a (meth)acrylamide structural unit, and also a further component having 2 to 6 polymerizable groups, this component also having alkylene oxide units. Following application of this material to a substrate, the film obtained therefrom can be provided with a pattern in the course of its curing by means of UV radiation, using a nickel embossing tool.

US 2007/0204953 A1 discloses a method for patterning adhesive resins, which provides in succession for application of a curable layer of adhesive resin to a substrate, the application of a structured pattern to said layer, and, subsequently, the curing of the layer, so as to give a substrate provided with a cured adhesive resin that comprises the desired patterning.

WO 2015/154866 A1 relates to a method for producing a substrate with a structured surface. In that case, first of all, a first UV-curing coating is applied to the substrate and is cured. Atop
5 this cured coating is then applied, as embossing varnish, a second UV-curing coating, which is embossed to generate a microstructure and is subsequently cured.

US 2015/166704 A1 discloses a microstructure-comprising cured
10 coating on a substrate, which coating is scratch-resistant.

DE 10 2007 062 123 A1 describes a method for applying an embossing varnish such as, for example, a UV-crosslinkable embossing varnish to a carrier film, structuring the embossing
15 varnish in the micrometer range, and curing the embossing varnish applied to the film to give an embossed film whose microstructure is subsequently modeled by deposition of a metal on the embossed surface, in other words by metalizing of the film. A disadvantage of such modeling by means of subsequent
20 metalization, however, is a resultant unwanted reduction in the quality of modeling.

Lastly, EP 2 146 805 B1 describes a method for producing a material having a textured surface. The method involves
25 providing a substrate with a curable coating, contacting said coating with a texturing medium for embossing, and then curing the coating embossed in this way and removing it from the texturing medium. The texturing medium comprises a surface layer which contains 20% to 50% of an acrylic oligomer, 15% to 35% of
30 a monofunctional monomer, and 20% to 50% of a polyfunctional monomer. WO 2016/090395 A1 and ACS Nano Journal, 2016, 10, pages 4926 to 4941 describe similar methods, with the explicit teaching in each case that in order to produce the surface layer of the texturing medium, large parts of triply ethoxylated
35 trimethylolpropane triacrylate (TMP(EO)₃TA) ought to be used in order to allow the generation of a comparatively hard die of the texturing medium. According to WO 2016/090395 A1, moreover, the coating composition used for producing the surface layer must

also necessarily include a structural unit which has at least two thiol groups, such as trimethylolpropane tris(3-mercaptopropionate), for example. The use of such thiols in corresponding coating material compositions is often
5 disadvantageous, however, since such compositions do not always have sufficient stability on storage and since coatings produced from them lack adequate weathering stability. A further factor is an odor nuisance, resulting from the use of the thiols, which of course is likewise undesirable.

10

The embossing methods known from the prior art, such as in particular the methods described in EP 2 146 805 B1, WO 2016/090395 A1, and ACS Nano Journal, 2016, 10, pages 4926 to 4941 are not always sufficiently capable, however, of
15 transferring embossments, particularly in the micrometer range and/or in the nanometer range, i.e. microstructures and/or nanostructures, particularly not without lowering the accuracy of modeling to an unacceptable degree in the case of such a transfer. At the same time, the embossments are not always
20 adequately replicated.

There is therefore a need for an embossing method which does not have the disadvantages stated above.

25 **Problem**

A problem addressed by the present invention is therefore that of providing a method for transferring embossed structures to coating compositions, and to substrates comprising such coating
30 compositions, and more particularly a process of this kind which allows the transfer of corresponding microstructures and/or nanostructures and which permits sufficient modeling accuracy in the transfer of the embossed structures, so that embossing is not accompanied by loss of any depth of modulation, and which
35 enables in particular the generation of a very largely reusable embossing die for transferring the embossed structures, and/or can be carried out using an embossing die of this kind. At the same time, it is to be possible for the embossing structures

that are to be transferred to be replicated to an extremely high degree, without the method featuring any disadvantages brought about in particular by unwanted or inadequate properties on the part of the coatings and coating compositions used, such as
5 inadequate adhesion, for example.

Solution

This problem is solved by the subject matter claimed in the
10 claims of the patent, and also by the preferred embodiments of that subject matter that are described in the description hereinafter.

A first subject of the present invention is therefore a method
15 for transferring an embossed structure according to claim 1.

With preference the parameter m in the at least three structural units of the formula (I), which are different from one another or are at least partially identical, in component (a) of the
20 coating composition (B1a), is in each case at least 2.

It has surprisingly been found that the method of the invention enables the transfer of embossed structures, more particularly microstructures and/or nanostructures, to the coating
25 composition (B2a) that is to be embossed, in a very high modeling accuracy, so that there is no loss of depth of modulation during embossing, with modeling taking place more particularly in a high accuracy in a range from 10 nm to 1000 µm structure width and in a range from 0.1 nm to 1000 µm structure depth. In this
30 context it has in particular been surprisingly found that the method of the invention enables transfer of embossed structures with a very high modeling accuracy and a high level of replication success with a composite (F1B1) which is obtainable by coating of a radiation-curable coating composition (B1a) onto
35 a preferably moving substrate (F1) and which is used as embossing die (p2) of the embossing tool (P2).

It has further been surprisingly found that the method of the

invention can be applied so advantageously because the coating (B1) of the composite (F1B1) employed, which is obtainable by coating of a radiation-curable coating composition (B1a) onto a preferably moving substrate (F1), is notable for high double
5 bond conversion. As a result, effective separation is enabled in particular between the composite (F2B2) and the embossing tool (P2) within the optional step (4) of the method of the invention. It has surprisingly been found, moreover, that the method of the invention can be applied so advantageously because
10 the coating (B1) on the substrate (F1) is distinguished by very good adhesion and for this reason as well a corresponding composite (F1B1) can be employed very effectively as embossing die (p2).

15 It has further been surprisingly found that the composite (F1B1) employable as embossing die (p2) of the embossing tool (P2) within the method of the invention can be reused for transferring the embossed structures such as microstructures and/or nanostructures, particularly in the form of a continuous
20 embossing die, this being advantageous for reasons of economics. Surprisingly, moreover, this composite (F1B1), which is present preferably in the form of a continuous embossing die (p2), not only is reusable and therefore multiply utilizable but also can be produced inexpensively and quickly on the large industrial
25 scale.

A further subject of the present invention is therefore also a composite (F1B1) according to claim 12.

30 With preference this composite (F1B1) is obtainable by implementation of the method steps (5) to (8), which are described in more detail below.

It has surprisingly been found that the at least partially
35 embossed composition (F1B1) of the invention not only can be employed as a reusable embossing die (p2), preferably as a reusable continuous embossing die (p2), in an embossing method such as the method of the invention, but also that by virtue of

the components present in the radiation-curable coating composition (B1a) used for producing this composite, it is possible to achieve very effective separation between the composite (F1B1), used as embossing die (p2) within the embossing tool (P2), and the embossed coating (B2) and/or a corresponding composite such as the composite (F2B2) comprising such an embossed coating like the coating (B2), especially when performing the method of the invention and within the optional step (4) therein. It has surprisingly been found, moreover, that the coating (B1) of the composite (F1B1) employed, which is obtainable by coating of a radiation-curable coating composition (B1a) onto a substrate (F1), is notable advantageously for a high double bond conversion such as a double bond conversion of $\geq 90\%$. It has further been found in particular that especially when traversing method steps (5) to (8) for producing the composite (F1B1), the embossed structure of the coating (B1) can be obtained with high modeling accuracy and high success of replication.

A further subject of the present invention, moreover, is a use of the composite (F1B1) of the invention according to claim 15.

Comprehensive description

The term "comprising" in the sense of the present invention, in connection with the coating compositions used in accordance with the invention, such as, for example, with the coating composition (B1a), and with the method of the invention and its method steps, preferably has the definition of "consisting of". With regard for example to the coating composition (B1a) employed in accordance with the invention - in addition to the components (a) and (b) and also (c) and optionally (d) - it is possible, moreover, for one or more of the other components identified below and optionally present in the coating composition (B1a) employed in accordance with the invention to be included in that composition. All the components may each be present in their preferred embodiments identified below. With regard to the method of the invention, it may have further

optional method steps in addition to steps (1-i) and (2-i) or (1-ii) and (2-ii) and also (3) and, optionally, (4), such as, for example, the steps (5) to (8).

5 Below and above, the first coating B1 is designated also as coating (B1), the second coating B2 also as coating (B2), the first coating composition B1a also as coating composition (B1a), the second coating composition B2a also as coating composition (B2a), the first substrate F1 also as substrate (F1), the second
10 substrate F2 also as substrate (F2), the first composite F1B1 also as composite (F1B1), the second composite F2B2aB1F1 also as composite (F2B2aB1F1), the third composite B2aB1F1 also as composite (B2aB1F1), the fourth composite F2B2B1F1 also as composite (F2B2B1F1), the fifth composite F2B2 also as composite
15 (F2B2) and the sixth composite F2B2a also as composite (F2B2a). Similarly, below and above, the first component a) is designated also as component (a), the second component b) also as component (b), the third component c) also as component (c) and the fourth component d) also as component (d). Similarly, below and above,
20 step 1-i) is designated also as step (1-i), step 1-ii) also as step (1-ii), step 2-i) also as step (2-i), step 2-ii) also as step (2-ii), step 3) also as step (3), step 4) also as step (4), step 5) also as step (5), step 6) also as step (6), step 7) also as step (7) and step 8) also as step (8).

25

Inventive method for transferring an embossed structure, comprising at least steps (1-i) and (2-i) or (1-ii) and (2-ii) and also (3) and optionally (4)

30 A first subject of the present invention is, as observed above, the method of the invention for transferring an embossed structure to at least a part of a surface of a coating composition (B2a). **Fig. 1** illustrates by way of example the steps (1-i) and (2-i) and also (3) and optionally (4) of the
35 method of the invention, as is also evident from the description of this figure below.

The method of the invention is preferably a continuous method.

The embossed structure is transferred or maintained by the at least partial embossing of the coating composition (B2a) applied at least partially to the surface of the substrate (F2), as per method step (2-i). An alternative possibility is that of transfer by means of the method steps (1-ii) and (2-ii). The term "embossing" refers to the at least partial furnishing of the coating composition (B2a), optionally as part of a composite (F2B2a), on at least a part of its surface with an embossed structure. In this case at least a certain area of the coating composition (B2a) is furnished with an embossed structure. Preferably the entire surface of the coating composition (B2a), optionally as part of the composite (F2B2a), is furnished with an embossed structure. Similar comments apply in connection with the term "embossing" with regard to the at least partially embossed composite (F1B1) employed as embossing die (p2), and composed of a substrate (F1) and of an at least partially embossed and at least partially cured coating (B1), which may be produced in accordance with steps (5) to (8) described below.

20

The embossed structures of the composites (F1B1), (F2B2a) and (F2B2) are based preferably and in each case independently of one another on a repeating and/or regularly arranged pattern. The structure in each case may be a continuous embossed structure such as a continuous groove structure or else a plurality of preferably repeating individual embossed structures. The respective individual embossed structures in this case may in turn be based preferably on a groove structure having more or less strongly pronounced ridges (embossed elevations) defining the embossed height of the embossed structure. In accordance with the respective geometry of the ridges of a preferably repeating individual embossed structure, a plan view may show a multiplicity of preferably repeating individual embossed structures, each of them different, such as, for example, preferably serpentine, sawtooth, hexagonal, diamond-shape, rhomboidal, parallelogrammatical, honeycomb, circular, punctiform, star-shaped, rope-shaped, reticular, polygonal, preferably triangular, tetragonal, more preferably rectangular

35

and square, pentagonal, hexagonal, heptagonal and octagonal, wire-shaped, ellipsoidal, oval and lattice-shape patterns, it also being possible for at least two patterns to be superimposed on one another. The ridges of the individual embossed structures
5 may also have a curvature, i.e., a convex and/or concave structure.

The respective embossed structure may be described by its width such as the width of the ridges, in other words by its structure
10 width, and by the height of the embossments, in other words by its structure height (or structure depth). The structure width such as the width of the ridges may have a length of up to one centimeter, but is preferably situated in a range from 10 nm to 1 mm. The structure height is situated preferably in a range
15 from 0.1 nm to 1 mm. Preferably, however, the respective embossed structure represents a microstructure and/or nanostructure. Microstructures here are structures - in terms both of structure width and of structure height - having characteristics in the micrometer range. Nanostructures here are
20 structures - in terms both of structure width and of structure height - having characteristics in the nanometer range. Microstructures and nanostructures here are structures which have a structure width in the nanometer range and a structure height in the micrometer range or vice-versa. The terms
25 "structure height" and "structure depth" are interchangeable here.

The structure width of the respective embossed structure is preferably situated in a range from 10 nm to 500 μm , more
30 preferably in a range from 25 nm to 400 μm , very preferably in a range from 50 nm to 250 μm , more particularly in a range from 100 nm to 100 μm . The structure height of the respective embossed structure is situated preferably in a range from 10 nm to 500 μm , more preferably in a range from 25 nm to 400 μm , very
35 preferably in a range from 50 nm to 300 μm , more particularly in a range from 100 nm to 200 μm . This is so for the embossed structures both of the composite (F1B1) and of the composite (F2B2).

The structure width and structure height of the respective embossed structure are determined here by mechanical scanning of the surface. In this case the embossed height is measured at
5 not less than 10 points on a line, distributed uniformly over the web width of the sample, taking care to ensure that the scanning instrument does not compress the embossed structure. The determination of the structure height represents a determination of the accuracy of modeling and is accomplished
10 by means of scanning force microscopy in accordance with the method described below.

Alternative (i) comprising steps (1-i) and (2-i)

15 The method of the invention as per alternative (i) comprises at least steps (1-i), (2-i) and (3) and also optionally (4).

Step (1-i)

20 Step (1-i) of the method of the invention provides for application of a coating composition (B2a) to at least a part of a surface of a substrate (F2). The substrate (F2) represents a carrier material for the coating composition (B2a) or the coating (B2) to be applied thereto.

25

The substrate (F2) or, if a coated substrate is used, the layer located on the surface of the substrate (F2) consists preferably of at least one thermoplastic polymer, selected more particularly from the group consisting of polymethyl
30 (meth)acrylates, polybutyl (meth)acrylates, polyethylene terephthalates, polybutylene terephthalates, polyvinylidene fluorides, polyvinyl chlorides, polyesters, including polycarbonates and polyvinyl acetate, preferably polyesters such as PBT and PET, polyamides, polyolefins such as polyethylene,
35 polypropylene, polystyrene, and also polybutadiene, polyacrylonitrile, polyacetal, polyacrylonitrile-ethylene-propylene-diene-styrene copolymers (A-EPDM), polyetherimides, phenolic resins, urea resins, melamine resins, alkyd resins,

epoxy resins, polyurethanes, including TPU, polyetherketones, polyphenylene sulfides, polyethers, polyvinyl alcohols, and mixtures thereof. Particularly preferred substrates or layers on the surface thereof are polyolefins such as, for example, PP (polypropylene), which may alternatively be isotactic, syndiotactic or atactic and may alternatively be unoriented or oriented through mono- or biaxial drawing, SAN (styrene-acrylonitrile copolymers), PC (polycarbonates), PMMA (polymethyl methacrylates), PBT (poly(butylene terephthalate)s), PA (polyamides), ASA (acrylonitrile-styrene-acrylic ester copolymers) and ABS (acrylonitrile-butadiene-styrene copolymers), and also their physical mixtures (blends). Particularly preferred are PP, SAN, ABS, ASA and also blends of ABS or ASA with PA or PBT or PC. Especially preferred is PET, PBT, PP, PE and polymethyl methacrylate (PMMA) or impact-modified PMMA. Especially preferred is a polyester, most preferably PET, for use as material of the substrate (F2). Alternatively the substrate (F2) itself - optionally in spite of a layer of at least one of the aforementioned polymers applied thereto - may be made of a different material such as glass, ceramic, metal, paper and/or fabric. In that case the substrate (F2) is preferably a plate and may be used, for example, in a roll-to-plate embossing apparatus.

The thickness of the substrate (F2) is preferably 2 μm up to 5 mm. Particularly preferred is a layer thickness of 25 to 1000 μm , more particularly 50 to 300 μm .

The substrate (F2) is preferably a film, more preferably a film web, very preferably a continuous film web. In that case the substrate (F2) may be used preferably in a roll-to-roll embossing apparatus.

In the sense of the present invention, the term "continuous film" or "continuous film web" refers preferably to a film having a length of 100 m to 10 km.

When step (1-i) is being carried out (and preferably also when

steps (2-i), (3) and (4) of the method are being carried out, and also when steps (1-ii), (2-ii), (3) and (4) of the method of alternative (ii) are being carried out), the substrate (F2) is preferably moving and is therefore a moving substrate. During
5 the implementation of step (1-i) and (2-ii), the substrate (F2) is preferably moved by means of a transport device such as a conveyor belt. The corresponding device used for implementing step (1-i) and also step (2-ii) therefore preferably comprises such a transport device. The corresponding device used for
10 implementing step (1-i) further comprises a means for applying the preferably radiation-curable coating composition (B2a) to at least a part of a surface of the substrate (F2). Similar comments apply in respect of the corresponding apparatus used for implementing step (2-ii).

15 *Step (2-i)*

Step (2-i) of the method of the invention provides for at least partial embossing of the coating composition (B2a), applied at
20 least partially to the surface of the substrate (F2), by means of at least one embossing tool (P2) comprising at least one embossing die (p2), the embossing die (p2) comprising a composition (B1F1) composed of a substrate (F1) and of an at least partially embossed and at least partially cured coating
25 (B1), and the product of the at least partial embossing being a composite (F2B2aB1F1). The embossing tool (P2) including the embossing die (p2) is preferably pressed at least partially onto the applied coating composition (B2a) during the implementation of step (2-i).

30 The embossing die (p2), used in step (2-i), of the embossing tool (P2) is preferably reusable and can be employed repeatedly for transferring at least one embossed structure, preferably within the method of the invention when the latter necessarily
35 comprises step (4). Step (2-i) preferably transfers microstructures and/or nanostructures as the embossed structure onto the coating composition (B2a).

The embossing die (p2), in other words the composite (F1B1), preferably comprises a film web (F1) which comprises an at least partially embossed and at least partially cured coating (B1). With particular preference the substrate (F1) is a continuous film web which comprises the at least partially embossed and at least partially cured coating (B1), thus making the composite (F1B1) used as embossing die (p2) a continuous embossing die, this being so especially when the substrate (F2) as well is a continuous film web.

The at least one embossing die (p2) of the embossing tool (P2) used for the at least partial embossing as per step (2-i) has a "negative structure" ("negative shape"), i.e., both the mirror image of the embossed structure possessed by the composite (F2B2), which is obtained after implementation of optional step (4) of the method of the invention and which is composed of a substrate (F2) and of an at least partially embossed and fully cured coating (B2), and the mirror image of the embossed structure of the embossing die (p1) of the embossing tool (P1).

The corresponding apparatus used for implementing step (2-i) comprises a means for at least partially embossing the coating composition (B2a), applied at least partially to the surface of the substrate (F2), by means of at least one embossing tool (P2). Additionally, the apparatus used preferably has a means for pressing (P2) onto the substrate (F2), used preferably as a continuous film web, after the application of the radiation-curable coating composition (B2a) to (F2), this means being positioned preferably downstream - as viewed in the conveying direction of the substrate (F2) - of the means for applying the radiation-curable coating composition (B2a).

The at least partial embossing as per step (2-i) of the method of the invention is carried out by means of an embossing tool (P2). (P2) may preferably be an embossing calender, which preferably comprises a grid application mechanism, more preferably a grid roll mechanism. This calender possesses rolls which are counter-rotating or co-rotating and are disposed

preferably above one another in the height direction with a defined spacing, and the composite (F2B2a) to be provided with an embossed structure is supplied to the rolls and passed through the roll nip which forms, the nip width being variably adjustable. The grid roll mechanism here preferably comprises a first roll such as a metallic roll, as for example a steel roll or a nickel roll, or else a quartz-based roll or a roll coated with at least one plastic. The first roll functions as embossing roll (press roll). The grid roll mechanism preferably comprises here a second roll (pressure application roll or pressing roll). The first roll here acts as an embossing tool (P2) and contains the negative form of the embossed structure to be embossed into the surface of the composite (F2B2a). For this purpose, the embossing tool (P2) is provided with a composite (F1B1) as embossing die (p2) which represents this negative shape. The negative shape of the structure to be embossed is produced on the embossing tool (P2) by the methods customary and known to the skilled person; depending on structure and materials, specific methods may be particularly advantageous. With preference this is accomplished in accordance with the invention by the embossing roll acting as an embossing tool (P2) and by the composite (F1B1) used as embossing die (p2) being in the form of a coated and at least partially embossed film, preferably film web, more preferably continuous film web which preferably is moving. The composite (F2B2a) to be embossed is moved in the opposing direction by means of the pressure application roll. At the point of the roll nip, which is formed by the counter-rotating rolls arranged with a defined distance from one another, embossing takes place as per step (2-i). The first roll, which guides the composite (F1B1) functioning as embossing die (p2) serves here for embossing the composite (F2B2a), which is guided by the second roll opposite this embossing roll, and which presses the composite (F2B2a) to be provided with an embossing structure against the first embossing roll. As already observed above, the structures on the embossing roll - that is, those of the embossing die (p2) - may either have a continuous structure or else may be designed as an interrupted structure (sequence of individual embossed structures), in which case a

combination of both structures is also possible. The respective structures on the embossing roll may have any of a very wide variety of geometric shapes, according to the intended structure of the composite. If necessary, step (2-i) may be carried out
5 at elevated temperature, e.g. at 30 to 100°C or at least up to 80°C. In that case the composite (F2B2a) to be embossed passes first through a heating roll mechanism, after which there may be irradiation with infrared light, before the actual embossing operation described above is accomplished. After embossing, the
10 composite (F2B2a) that is then embossed runs optionally through a chill roll mechanism for cooling. Alternatively, step (2-i) may also take place with cooling: in that case, the composite (F2B2a) to be embossed runs first through a chill roll mechanism before the above-described actual embossing operation takes
15 place.

The composition (F1B1) used as embossing die (p2) in step (2-i) is preferably a composite composed of a film web (F1) and of an at least partially embossed and at least partially cured coating
20 (B1) applied thereto.

During the implementation of step (2-i), the composite (F1B1) used as embossing die (p2) in step (2-i) is preferably guided via a first roll functioning as embossing tool (P2), and the
25 composite (F2B2a) is guided over a second roll, which is opposite the first roll and is counter-rotating thereto or co-rotating therewith, preferably counter-rotating.

The at least partial embossing as per step (2-i) takes place
30 preferably at the level of the roll nip formed by the two mutually opposing rolls, rotating counter-directionally or in the same direction, and the at least partially embossed coating (B1) of the composite (B1F1) is facing the coating composition (B2a) of the composite (F2B2a). The at least partial embossing
35 here is accomplished preferably by pressing of the composite (F1B1) onto the composite (F2B2a).

The composite (F1B1) used as embossing die (p2) in step (2-i)

and made up of substrate (F1) and at least partially embossed and at least partially cured coating (B1), is also referred to below as "master substrate" or "master film". Where the substrate (F1) is a film, the corresponding master film is referred to as "master foil". Where the substrate (F1) is a foil web, the corresponding master film is referred to as "master foil web". The coating (B1) of the master film is also referred to hereinafter as "at least partially cured master coating" or "master coating film", and the coating composition (B1a) used for producing the cured master coating is referred to as "master coating". Between (F1) and (B1) in the composite (F1B1) there is preferably no further (coating) layer. It is possible, however, for there to be at least one adhesion promoter layer present between (F1) and (B1) of the composite (F1B1), this layer in this case being preferably permeable to UV radiation.

The composite (F1B1) used as embossing die can optionally be pretreated with the coating composition (B2a) employed before carrying out step (2-i). Such a pretreatment comprises or is preferably a wetting of the embossing die with the coating composition (B2a).

Step (3)

Step (3) of the method of the invention provides for at least partial curing of the coating composition (B2a), within the composite (F2B2aB1F1) obtained after step (2-i) or step (2-ii), to give a composite (F2B2B1F1); throughout the duration of the at least partial curing, the coating composition (B2a) is in contact with the partial assembly (B1F1) used as embossing die (p2) within the composite (F2B2aB1F1).

Steps (2-i) and (3) are preferably carried out concurrently. In that case the at least partial curing as per step (3) takes place preferably *in situ* during the implementation of step (2-i).

The corresponding apparatus used in implementing step (3)

therefore preferably comprises at least one radiation source for irradiating the coating composition (B2a) with a curative radiation. Since the coating composition (B2a) is preferably a UV-curable coating composition, the curative radiation used is preferably UV radiation. If the coating composition (B2a) is not radiation-curable, it is preferably chemically curable. In that case the curing of step (3) takes place thermally, by use of suitable thermal radiation sources, for example. Also possible, of course, is combined curing, i.e., thermal curing and curing by means of UV radiation.

Examples of suitable radiation sources of the radiative curing include low-pressure, medium-pressure and high-pressure mercury emitters and also fluorescent tubes, pulsed emitters, metal halide emitters (halogen lamps), lasers, LEDs and, moreover, electronic flash installations, enabling radiative curing without a photoinitiator, or excimer emitters. Radiative curing takes place through exposure to high-energy radiation, i.e., UV radiation or daylight, or by bombardment with high-energy electrons. The radiation dose typically sufficient for crosslinking in the case of UV curing is in the range from 80 to 3000 mJ/cm². It is of course also possible to use two or more radiation sources for the curing - two to four, for example. These sources may also each emit in different wavelength ranges.

The at least partial curing in step (3) takes place preferably by irradiation through the substrate (F2). In that case it is advantageous for the permeability of the substrate (F2) to the radiation used to be harmonized with that of the at least one photoinitiator used, present preferably in the coating composition (B2a). Thus, for example, the material PET as substrate (F2), hence a PET film, for example, is permeable to radiation having a wavelength of below 400 nm. Photoinitiators which generate radicals with such radiation include, for example, 2,4,6-trimethylbenzoyldiphenylphosphine oxide, ethyl 2,4,6-trimethylbenzoylphenylphosphinate and bis(2,4,6-trimethylbenzoyl)phenylphosphine oxide. In this case, therefore, there is preferably at least one such photoinitiator

present in the coating composition (B2a).

Optional step (4)

5 Step (4) in the method of the invention provides for optional removal of the composite (F2B2) within the composition (F2B2B1F1) from the composite (B1F1) used as embossing die (p2). Accordingly, a composite (F2B2) can be obtained, composed of substrate (F2) and of at least partially embossed and at least
10 partially cured coating (B2). With preference, step (4) is implemented.

Alternative (ii)

15 The method of the invention according to alternative (ii) comprises at least the steps (1-ii), (2-ii) and (3) and also, optionally, (4). Steps (3) and (4) have already been described above in connection with alternative (i).

20 *Step (1-ii)*

Step (1-ii) of the method of the invention provides for application of a coating composition (B2a), to at least a part of an at least partially embossed surface of a composite (B1F1),
25 employed as an embossing die (p2) of an embossing tool (P2), composed of a substrate (F1) and of an at least partially embossed and at least partially cured coating (B1), to give a composite (B2aB1F1).

30 The composite (F1B1) used as embossing die can optionally be pretreated with the coating composition (B2a) employed before carrying out step (1-ii). Such a pretreatment comprises or is preferably a wetting of the embossing die with the coating composition (B2a).

35

Step (2-ii)

Step (2-ii) of the method of the invention provides for

application of a substrate (F2) to at least a part of the surface, formed by (B2a), of the composite (B2aB1F1), to give a composite (F2B2aB1F1).

- 5 Preferably, the composite (B1F1) used as embossing die (p2) in step (1-ii), following the application of the coating composition (B2a) to at least a part of its at least partially embossed surface, to give the composite (B2aB1F1), is guided, during the implementation of step (2-ii), over a first roll
10 which functions as embossing tool (P2), and the substrate (F2) used within step (2-ii) is guided via a second roll, which is opposite to the first roll and is counter-rotatory thereto or is co-rotatory therewith, preferably counter-rotatory.
- 15 The at least partial embossing as per step (2-ii) takes place preferably at the level of the roll nip formed by the two mutually opposed rolls, rotating counter-directionally or in the same direction, with the coating composition (B2a) of the composite (B2aB1F1) facing the substrate (F2). The at least
20 partial embossing in this case is achieved preferably by pressuring or pressing of the substrate (F2) onto the composite (B2aB1F1).

Fig. 1 shows schematically a side view of an apparatus which can
25 be used to implement steps (1-i) and (2-i) and also (3) and optionally (4) of the method of the invention and which is used for exemplary illustration of the method of the invention. This apparatus may equally be employed, in a fundamentally analogous way, to implement steps (1-ii) and (2-ii) and also (3) and
30 optionally (4) of the method of the invention as well. By means of this apparatus it is possible to transfer structures such as microstructures and/or nanostructures preferably from an embossing die (F1B1, p2) present as master film onto a substrate (F2) coated with (B2a). This apparatus is therefore also
35 referred to generally as a transfer apparatus and is given the reference symbol (10) in **Fig. 1**.

The core of the transfer apparatus (10) is an embossing region

(1) in which there is arranged a press roll (2) having a roll jacket made of fused silica. The press roll (2) is driven for rotation. Arranged alongside the press roll (2) is a radiation source in the form of lighting unit (3), which generates UV light and may in particular comprise a row of UV-LEDs disposed in the lengthwise direction of the press roll (2). As shown in **Fig. 1**, the lighting unit (3) may also be disposed in the interior of the press roll (2). Arranged in a manner pressed against the press roll (2) is a pressuring roll (4), in the embossing region (1). In a die frame (5) of the transfer apparatus (10) there are two film web rollers (6) and (7) arranged, which can be motor-driven for rotation. Of course, the film web rollers (6) and (7) can also be mounted and arranged otherwise than in a die frame (5), e.g., in a cabinet element or else outside the actual transfer apparatus (10). Rolled onto the film web rollers (6) and (7), which here are shown as disposed in the die frame, is a master film web (8) which represents a continuous embossing die. On a transfer surface, the master film web (8) is provided with a master coating layer, which features negative shapes, as a surface relief, of microstructures and/or nanostructures that are to be transferred. The master coating layer is at least partially cured, and so the relief-like structurings within it are stable. The master film web (8) can be obtained by implementation of steps (5) to (8) of the method of the invention, and thus constitutes a composite (F1B1). The master film web (8) runs off from the first film web roller (6), is supplied via various deflection roller systems to the embossing region (1), and runs, as is evident in **Fig. 1**, perpendicularly from above into the region between the press roll (2) and the pressuring roll (4). In that region it is guided in taut contact over a section of the periphery of the press roll (2), and then leaves the press roll (2) again and is supplied, once more via deflection roller systems with web tensioners, to the second film web roller (7), on which it is wound. A film web (9) forming the substrate (F2), which is to be provided with structures such as microstructures and/or nanostructures, is supplied, starting from a film web roller (11), here again via various deflection roller systems

with web tighteners, to the embossing region (1), where it runs tautly over a peripheral section of the pressuring roll (4), from where it enters into the region of the contact of the pressuring roll (4) on the press roll (2) or into the region of the roll nip formed between these elements. The film web (9) leaves this region, in the representation of **Fig. 1**, perpendicularly downward and is guided - again guided via deflection roller systems and web tighteners - to a film web roller (12), on which it is wound up as a fully treated product.

On its path into the embossing region (1) or on to the roll nip between the press roll (2) and the pressuring roll (4), the film web (9) is provided with a coating layer on its surface facing the press roll (2) in the press region (1), by means of a coating application unit (27), which in this case is disposed outside the press region (1). The coating application unit (27) therefore applies a coating composition (B2a) to the film web (9) used as (F2) in accordance with step (1-i) of the method of the invention. In the press region (1), the film web (9) is then brought together, by its surface provided with the as yet uncured coating layer, with the surface, provided with the master coating layer, of the master film web (8), in order to implement step (2-i) of the method of the invention. In this case the film web (9) runs via the pressuring roller (4), and the master film web (8) runs via the press roll (2). Both webs, the film web (9) and the master film web (8), are facing one another with their surfaces provided with the respective coating layer (in the case of the master film web (8), the at least partially cured master coating layer, corresponding to the coating (B1); in the case of the film web (9), the uncured coating layer, corresponding to the coating composition (B2a)). In the region in which the pressuring roll (4) is pressed against the press roll (2), the negative image of the structures to be transferred, such as microstructures and/or nanostructures, which is formed in the master coating layer (B1) is impressed into the uncured coating layer corresponding to the coating composition (B2a), and the structures are transferred as a result. At the same time, the lighting unit (2) performs UV illumination and therefore implements at least partial curing of the uncured coating layer,

corresponding to the coating composition (B2a) of the coating layer on the film web (9), for as long as this coating layer is still in contact with the master coating layer (8). Accordingly, directly during transfer of the structures and *in situ*, the at least partial curing of the coating layer is carried out. The irradiation of the film web (9), or of the uncured coating layer applied thereon, is accomplished here through the film material (9) in the case of irradiation from outside onto the press cylinder (2). Alternatively, irradiation takes place through the fused silica material of the outer surface of the press cylinder (2) and also through the material of the master film web (8) and of the master coating layer applied thereon. Accordingly, master film web (8) and master coating layer are designed so as to be permeable to the radiation used, in this case UV light. The outer surface of the press roll (2) is described here as consisting of fused silica. Any other material, however, is also suitable here in principle, provided that it is permeable to the curative radiation (which may be other than UV light) emitted from the interior of the press roll (2). Alternatively, instead of the lighting unit (3) which supplies UV illumination, it is also possible, for example, to use a thermal emitter if the coating composition (B2a) is a non-radiation-curing coating composition. A possibility following the at least partial curing by UV elimination is a postexposure, by means of IR radiation, for example. At the end of this curing operation as per optional step (4) of the method of the invention, the film web (9) and the master film web (8) part from one another, with parting of the now structured layer composites (F2B2) and master film (F1B1). The coated film web (9) thus provided with the desired structuring (i.e., the composite (F2B2)) is supplied as a completed product to the film web roller (12) and is wound up on that roller. If there is illumination by means of a lighting unit (3) from outside onto the press roll (2), then the coated film web (9) provided with a desired structure (i.e., the composite (F2B2)) may also be opaque, if the arrangement is selected such that the master film web (8) (i.e., the composite (F1B1)) and the film web (9) (i.e., the composite (F2B2)) are switched. The coating of the coating application unit (27) in

accordance with step (1-i) of the method of the invention may then take place without restriction of the operation onto the master film web (8).

5 *Optional steps (5) to (8) of the method of the invention for producing the composite (F1B1) used as embossing die (p2)*

The composite (F1B1) used in step (2-i) and step (1-ii) of the method, and composed of a substrate (F1) and of an at least
10 partially embossed and at least partially cured coating (B1), is preferably at least obtainable by steps (5) to (8) as specified in more detail hereinafter. Steps (5) to (8) of the method of the invention are therefore carried out for producing the composite (F1B1) used as embossing die (p2). **Fig. 2** provides
15 an exemplary illustration of steps (5) to (8) of the method of the invention, as is also evident from the description of this figure below.

Step (5)

20

Step (5) of the method of the invention provides for application of a radiation-curable coating composition (B1a) to at least a part of a surface of a substrate (F1). The substrate (F1) constitutes a carrier material for the coating composition (B1a)
25 or coating (B1) to be applied thereto. The substrate (F1) may have been coated. Suitable material for the substrate (F1) or for the surface layer thereof comprises the same materials which can also be used for producing the substrate (F2) and have already been mentioned above. Reference is hereby made
30 explicitly to the corresponding passages. The substrate (F1) is preferably a film, more preferably a film web, very preferably a continuous film web. Preferred material for the substrate (F1) is polyester, more particularly PET. The thickness of the substrate (F1) is preferably 2 μm up to 5 mm. Particularly
35 preferred is a layer thickness of 25 to 1000 μm , more particularly 50 to 300 μm .

During implementation of step (5) (and preferably also during

implementation of steps (6), (7) and (8) of the method) the substrate (F1) is preferably moving and is therefore a moving substrate. During the implementation of step (5), the substrate (F1) is moved preferably by means of a transport means such as
5 a conveyor belt. The corresponding apparatus used for implementing step (5) therefore preferably comprises a transport means of this kind. The corresponding apparatus used for implementing step (5) further comprises a means for applying the preferably radiation-curable coating composition (B1a) to at
10 least a part of a surface of the substrate (F1).

Step (6)

Step (6) of the method of the invention provides for at least
15 partial embossing of the coating composition (B1a), applied at least partly to the surface of the substrate (F1), by means of at least one embossing tool (P1) having at least one embossing die (p1). The at least partial embossing transfers an embossed structure at least partially to the surface of the coating
20 composition (B1a) applied to the substrate (F1). The term "embossing" has already been defined above. Accordingly, it refers, in connection with (B1a) or (B1), to the at least partial furnishing of the coating composition (B1a) as part of the composite (F1B1a), with an embossed structure. In this case at
25 least a certain area of the coating composition (B1a) is furnished with an embossed structure. With preference the entire surface of the coating composition (B1a), as part of the composite (F1B1a), is furnished with an embossed structure. During the implementation of step (6), the embossing tool (P1)
30 is preferably pressured or pressed at least partly onto the applied coating composition (B1a).

Step (6) preferably transfers microstructures and/or nanostructures as embossed structure onto the coating
35 composition (B1a).

The corresponding apparatus used for implementing step (6) therefore comprises a means for at least partially embossing the

coating composition (B1a), applied at least partially to the surface of the substrate (F1), by means of at least one embossing tool (P1). The apparatus used preferably further comprises a means for pressing (P1) onto the substrate (F1), used preferably in the form of continuous film web, after the application of the radiation-curable coating composition (B1a) to (F1), this means being situated preferably downstream of the means for applying the radiation-curable coating composition (B1a), as viewed in the direction of conveying of the substrate (F1).

The at least partial embossing as per step (6) of the method of the invention is carried out by means of an embossing tool (P1). (P1) may preferably be an embossing calender, which preferably comprises a grid application mechanism, more preferably a grid roll mechanism. This calender possesses counter-rotating rolls, preferably arranged above one another in the height direction with a certain spacing, and the composite (F1B1a) to be provided with an embossed structure is supplied to the rolls and is guided through the roll nip which forms, with the nip width being variably adjustable. The grid roll mechanism here preferably comprises a first roll such as a metallic roll, as for example a steel roll or nickel roll, and a second roll. The first roll (embossing roll) functions here as the embossing tool (P1) and contains the negative form of the embossed structure to be embossed into the surface of the composite (F1B1a). This corresponds to the positive structure which is to be embossed into the composite (F2B2a) in step (2) of the method. The second roll serves as an impression or pressing roll. The positive form of the structure to be embossed is produced on the embossing tool (P1) according to the methods customary and known to the skilled person; depending on structure and materials, specific methods may be particularly advantageous. In accordance with the invention this is preferably realized by the embossing roll acting as embossing tool (P1) and comprising an embossing die (p1). The composite (F1B1a) to be embossed, in the form for example of a film web coated at least partially with (B1a), is moved counter-directionally by means of the pressuring roll. At the point of the roll nip formed by the counter-rotating rolls

disposed with a certain distance from one another, embossing takes place in accordance with step (6). The first roll, which carries the embossing die (p1), serves here for embossing the composite (F1B1a) which is guided by the second roll, opposite
5 this embossing roll, with the second roll pressing the composite (F1B1a), to be provided with an embossed structure, against the first embossing roll. If necessary, step (6) may be carried out at elevated temperature, as for example at 30 to 100°C or up to 80°C. In this case, the composite (F1B1a) for embossing runs
10 first through a heating roll mechanism, followed optionally by irradiation with infrared light, before the actual embossing procedure, described above, takes place. After the embossing, the composite (F1B1a), which is then embossed, runs optionally through a cooling roll mechanism for cooling. Alternatively,
15 step (6) may also take place with cooling: in this case, the composite (F1B1a) for embossing runs first through a cooling roll mechanism, before the actual embossing procedure described above takes place. The embossing tool (P1) used may also be a conventional press cylinder, which carries the negative form of
20 the embossed structure to be embossed into the surface of the composite (F1B1a). This cylinder can be pressed onto the composite (F1B1a) for the at least partial embossing.

The at least one embossing die (p1) of the embossing tool (P1)
25 used for at least partially embossing in accordance with step (6) has a "positive structure" ("positive form"), i.e., it has the embossed structure exhibited by the composite (F2B2), which is obtained after implementation of step (4) of the method of the invention and which is composed of a substrate (F2) and of
30 an at least partially embossed and fully cured coating (B2). The embossing tool (P1) is preferably a metallic embossing tool, more preferably made of nickel. Accordingly, the embossing die (p1) is preferably metallic, more preferably made of nickel, more particularly made of nickel which contains small amounts
35 of phosphorus. Alternatively, however, soft materials such as polydimethylsiloxanes (PDMS), for example, may also be used for producing (p1). Moreover, rolls may be employed that are coated with at least one plastic. Furthermore, the embossing tool (P1)

may have a structured coating such as a UV coating as embossing die. The coating composition (B1a) applied to (F1) exhibits a negative form of the embossed structure to be transferred, such as microstructures and/or nanostructures, after step (6) has
5 been implemented.

The embossing die of the embossing tool used can optionally be pretreated with the coating composition (B1a) employed before carrying out step (6). Such a pretreatment comprises or is
10 preferably a wetting of the embossing die with the coating composition (B1a).

Step (7)

15 Step (7) of the method of the invention provides for at least partial and preferably complete curing of the coating composition (B1a), applied to at least a part of the surface of the substrate (F1) and at least partially embossed, to give a composite (F1B1) composed of substrate (F1) and of at least
20 partially embossed and at least partially cured coating (P1); throughout the duration of the at least partial curing, the coating composition (B1a) is in contact with the at least one embossing die (p1) of the at least one embossing tool (P1).

25 Steps (6) and (7) are preferably carried out concurrently. In that case the curing as per step (7) takes place preferably *in situ* during the implementation of step (6).

The corresponding apparatus used for implementing step (7)
30 therefore preferably comprises at least one radiation source for irradiating the radiation-curable coating composition (B1a) with a curative radiation, preferably UV radiation.

Examples of suitable radiation sources for the radiative curing
35 include low-pressure, medium-pressure and high-pressure mercury emitters and also fluorescent tubes, pulsed emitters, metal halide emitters (halogen lamps), lasers, LEDs and, moreover, electronic flash installations, enabling radiative curing

without a photoinitiator, or excimer emitters. Radiative curing takes place through exposure to high-energy radiation, i.e., UV radiation or daylight, or by bombardment with high-energy electrons. The radiation dose typically sufficient for crosslinking in the case of UV curing is in the range from 80 to 3000 mJ/cm². It is of course also possible to use two or more radiation sources for the curing - two to four, for example. These sources may also each emit in different wavelength ranges.

The curing in step (7) takes place preferably by irradiation through the substrate (F1). In that case it is advantageous for the permeability of the substrate (F1) to the radiation used to be harmonized with that of the at least one photoinitiator used as component (c). Thus, for example, the material PET as substrate (F1), hence a PET film, for example, is permeable to radiation having a wavelength of below 400 nm. Photoinitiators which generate radicals with such radiation include, for example, 2,4,6-trimethylbenzoyldiphenylphosphine oxide, ethyl 2,4,6-trimethylbenzoylphenylphosphinate and bis(2,4,6-trimethylbenzoyl)phenylphosphine oxide.

Step (8)

Step (8) of the method of the invention provides for removal of the composite (F1B1) from the embossing tool (P1), so producing the desired product, namely the composite (F1B1) used as embossing die (p2) and composed of substrate (F1) and of at least partially embossed and at least partially cured coating (B1).

Fig. 2 shows schematically a side view of an apparatus which can be used for implementing steps (5) to (8) of the method of the invention for producing a composite (F1B1) used as (p2), i.e., for producing a master film, and which is used for exemplary illustration of the method of the invention in relation to steps (5) to (8). By means of this apparatus it is possible to transfer structures such as microstructures and/or nanostructures, by means of an embossing tool (P1), to a substrate (F1) coated with

(B1a), and, after at least partial curing, to produce a composite (F1B1) - referred to as master film web (8) within **Fig. 2** - which can be used as master film, this composite being able to be used as embossing die (p2) as described above in the method
5 illustrated in association with **Fig. 1**.

The master transfer apparatus (30) shown in **Fig. 2** operates according to a transfer principle wherein the desired negative structures are embossed directly, from a structured press
10 cylinder or a press roll, which here is a master press cylinder (17), into the as yet uncured coating layer applied to the master film web (8b), corresponding to a composite (F1B1a), and this coating layer is then at least partially cured, with the structures applied thereon, curing taking place *in situ* by means
15 of a lighting unit (3), to give the master film web (8) - corresponding to a composite (F1B1). In this method, the film web (8a) used as substrate (F1) is drawn off from a film web roller (18), which contains only the carrier material, in other words the pure film without applied master coating, and is guided
20 via various deflection roller systems and web tensioning systems, and is introduced into an embossing region (1) of the apparatus. There, the film web (8a) runs into a region between a pressuring roll (4) and the master press cylinder (17), and is provided outside the press region, in the coating application
25 means (27), with the as yet uncured master coating layer (corresponding to the coating composition (B1a)). This application of coating corresponds to step (5) of the method of the invention. In the embossing region (1), in which the master film web (8b) with the as yet uncured master coating layer runs
30 along a section of the outer surface of the master press cylinder (17), the microstructures and/or nanostructures embossed into the outer surface of the master press cylinder (17) are introduced as a negative image into the master coating layer of the master film web (8b) and are transferred. This corresponds
35 to step (6) of the method of the invention. The master film web (8b) comprising the uncured coating composition (B1a) is then at least partially cured, in accordance with step (7) of the method of the invention. Curing here takes place *in situ* by

irradiation with a lighting unit (3), by means of UV radiation, as for example by means of a unit formed of UV-LEDs. The resulting master film (8), in other words the composite (F1B1), is subsequently taken off, in accordance with step (8) of the method of the invention, from the outer surface of the master press cylinder (17), and the master film web (8) thus completed is spooled up onto a film web roller (19). The film web roller (19) then contains the completed master film web (8) with the master coating layer applied thereon and with the negative images of the microstructures and/or nanostructures embossed therein. This film web roller (19) can be removed and then used as first film web roller (6) in a transfer apparatus (10) in accordance with **Fig. 1** or in another transfer apparatus operating with the same principle.

Inventively employed coating compositions (B1a) and (B2a)

Coating composition (B1a)

The coating composition (B1a) is a radiation-curable coating composition. The terms "radiation-curable" and "radiation-curing" are interchangeable here. The term "radiation curing" refers preferably to radical polymerization of polymerizable compounds by virtue of electromagnetic and/or particulate radiation, examples being (N)IR light in the wavelength range of $\lambda \geq 400$ -1200 nm, preferably 700-900 nm, and/or UV light in the wavelength range of $\lambda = 100$ to 400 nm, preferably of $\lambda = 200$ to 400 nm and more preferably $\lambda = 250$ to 400 nm, and/or electronic radiation in the range from 150 to 300 keV and more preferably with a radiation dose of at least 80, preferably 80 to 3000 mJ/cm². Radiation curing employed with particular preference is UV radiation. The coating composition (B1a) may be cured by use of a suitable radiation source. Consequently, (B1a) is preferably a UV radiation-curing coating composition.

The coating composition (B1a) comprises

the at least one component (a) in an amount in a range from 40

to 95 wt%, preferably in a range from 45 or > 45 to 90 wt%, more preferably in a range from 50 or > 50 such as 55 to 85 wt%, very preferably in a range from 55 or 60 to 80 wt%,

5 the at least one additive as component (b) in an amount in a range from 0.01 to 5 wt%, preferably in a range from 0.05 to 4.5 wt%, more preferably in a range from 0.1 to 4 wt%, very preferably in a range from 0.2 or 0.5 to 3 wt%,

10 at least one photoinitiator as component (c) in an amount in a range from 0.01 to 15 wt%, preferably in a range from 0.1 to 12 wt%, more preferably in a range from 0.5 to 10 wt%,

the at least one component (d), having at least one carbon double
15 bond, in an amount in a range from 0 to 45 wt%, preferably in a range from 0 to 40 wt%, more preferably in a range from 0 to 35 wt%, very preferably in a range from 0 to 30 wt%,

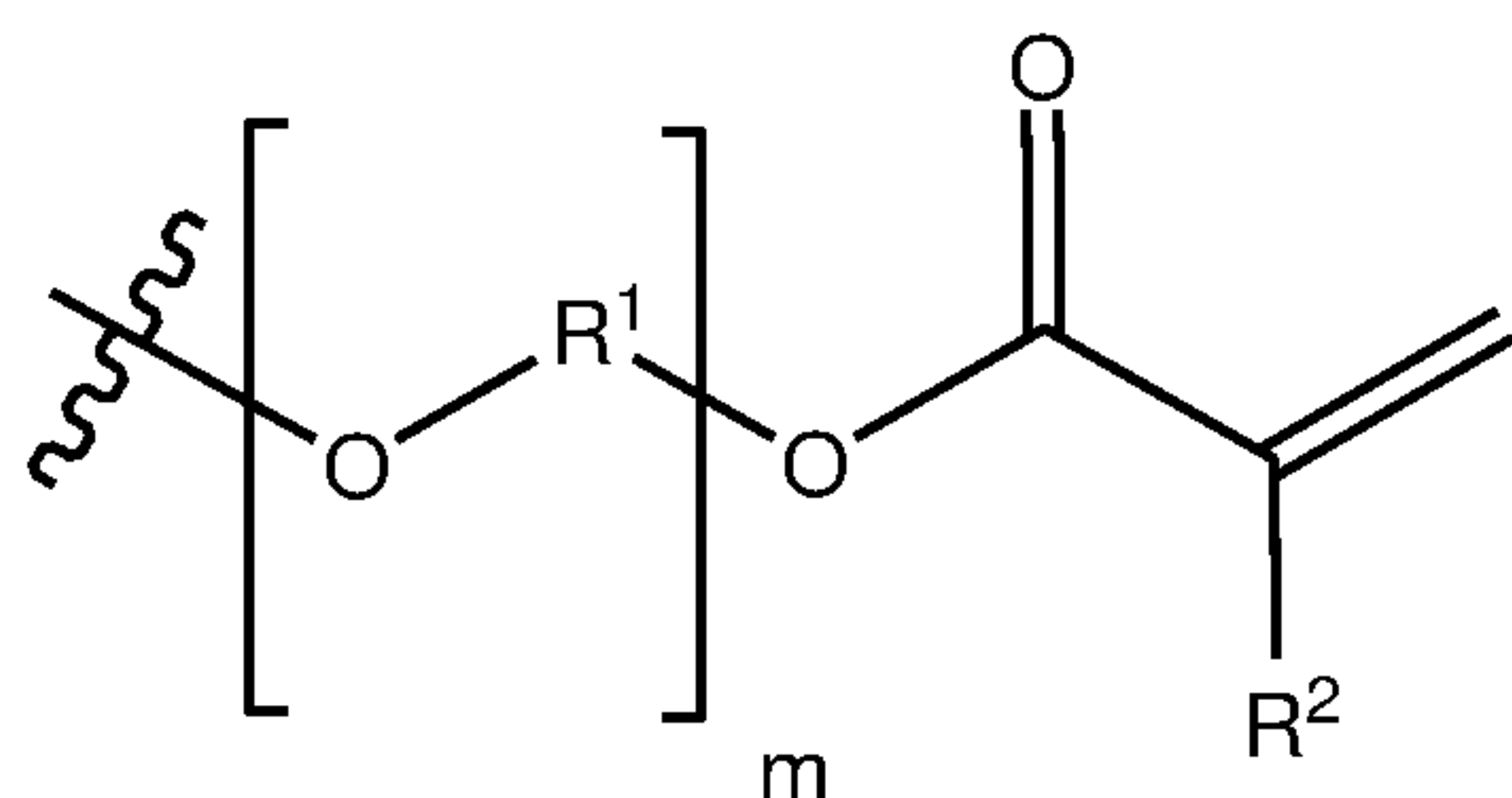
based in each case on the total weight of the coating composition
20 (B1a).

The presence of component (d) in the inventively employed coating composition (B1a) is therefore merely optional, as evident from the lower limit of 0 wt% indicated respectively
25 above. With preference, the coating composition (B1a) contains component (d) in an amount of up to 30 wt%, based on the total weight of the coating composition (B1a).

The components (a), (b), (c) and (d) are each different from one
30 another. The stated amounts of the components (a), (b), (c) and (d) are based in each case on the total weight of the coating composition (B1a). The amounts of all the components present in the coating composition (B1a), i.e., the amounts of components (a), (b) and (c) and also optionally (d), and also of further
35 components optionally present, in (B1a) add up to 100 wt%.

Component (a) has at least three structural units, in each case different from one another or at least partially identical, of

the formula (I)



(I),

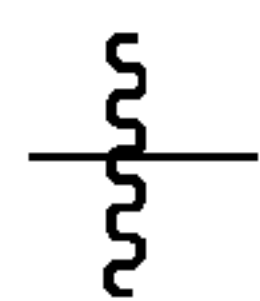
5 in which

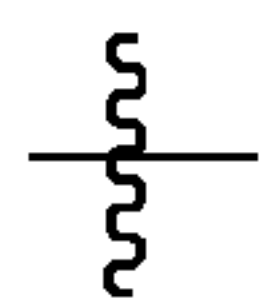
the radicals R^1 each independently of one another are a C_2 - C_8 alkylene group,

10 the radicals R^2 each independently of one another are H or methyl, and

the parameters m each independently of one another are an integral parameter in a range from 1 to 15, preferably in a
 15 range from 1 to 10, more preferably in a range from 1 to 8 or 2 to 8, very preferably in a range from 1 to 6 or 2 to 6, more particularly in a range from 1 to 4 or 2 to 4, but with the proviso that in at least one of the structural units of the formula (I) the parameter m is at least 2, preferably at least
 20 3.

Component (a) preferably has at least three identical structural units of the formula (I).



25 The symbol "  " here stands for a bond of the respective radical to the superordinate structure of the component (a) - in other words, for example, for a bond of the radical $-[O-R^1]_m-O-C(=O)-C(R^2)=CH_2$ within the structural unit of the formula (I) to the superordinate structure of the component (a). This bonding takes
 30 place preferably via a linking of the oxygen atom of the radical $-[O-R^1]_m-$ to a carbon atom of the superordinate radical. Similar comments apply in respect of the other structural units of the

formula (I). It is clear that all of the at least three structural units of the formula (I) are combined within a single component - specifically component (a).

- 5 The component (a) preferably has precisely three structural units of the formula (I). In that case component (a) has precisely three functional (meth)acrylic groups. Alternatively, the structural units of the formulae (I) may each also be present more than three times as part of the component (a). In that
10 case, for example component (a) may have more than three functional (meth)acrylic groups, as for example 4, 5 or 6 (meth)acrylic groups.

The aforementioned radicals R^1 each independently of one another
15 are a C_2 - C_8 alkylene group, preferably a C_2 - C_6 alkylene group, more preferably a C_2 - C_4 alkylene group, very preferably, each independently of one another, an ethylene group and/or a propylene group, especially preferably ethylene. In particular, all radicals R^1 are ethylene. Suitable as propylene groups in
20 each case are radicals R^1 which have a structure $-CH_2-CH_2-CH_2-$ or a structure $-CH(CH_3)-CH_2-$ or a structure $-CH_2-CH(CH_3)-$. Particularly preferred in each case, however, is the propylene structure $-CH_2-CH_2-CH_2-$.

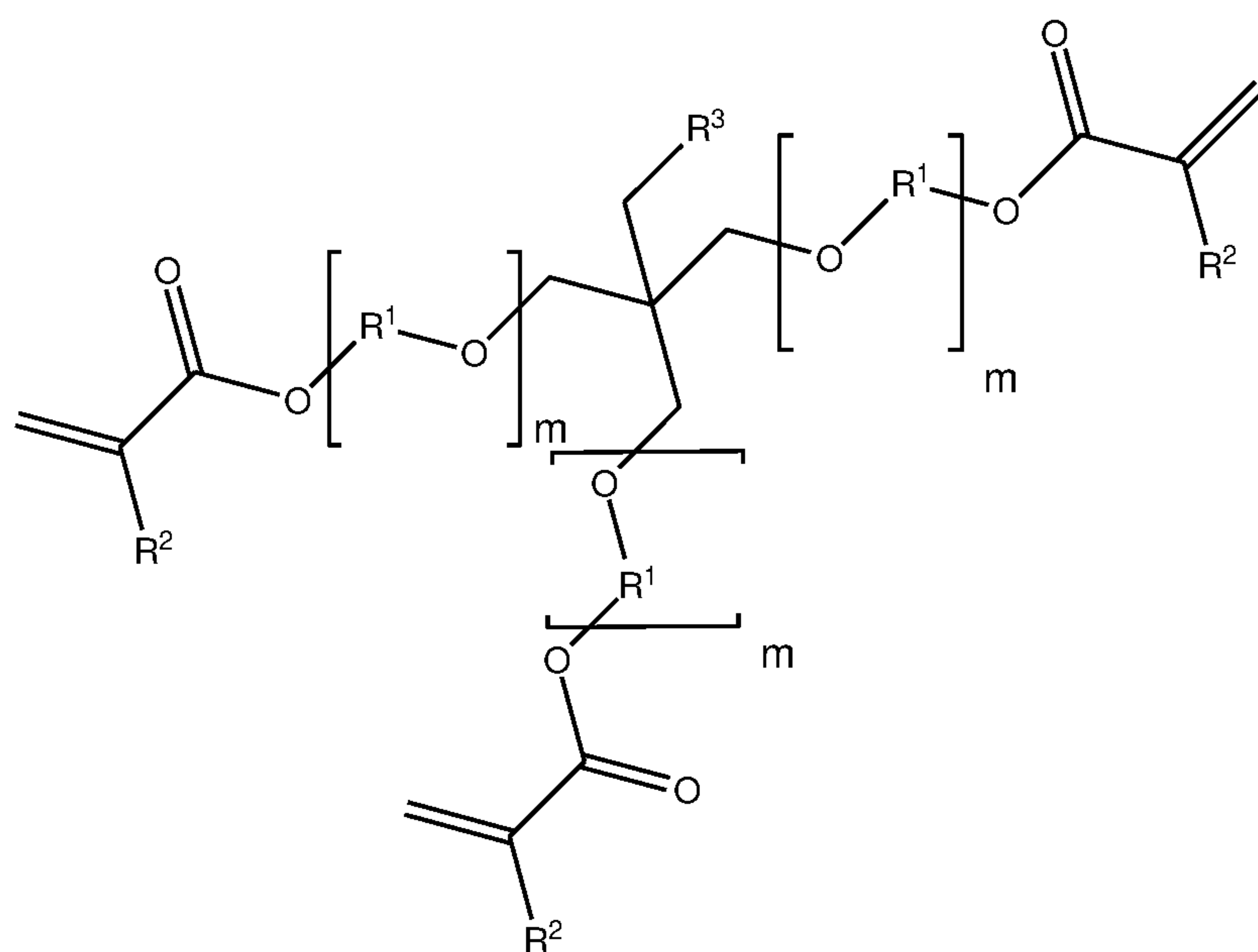
- 25 The parameters m , in each case independently of one another, are an integer in a range from 1 to 15. Since component (a) has at least three of the structural units of the formula (I), and since the parameter m is at least 2 in at least one of the structural units of the formula (I), component (a) includes a
30 total of at least four ether groups of the general formula " $-O-R^1-$ ".

With preference component (a) in total has at least five, more preferably at least six, ether groups of the general formula
35 " $-O-R^1-$ ". The number of ether groups of the general formula " $-O-R^1-$ " within component (a) is situated preferably in a range from 4 to 18, more preferably in a range from 5 to 15, very preferably in a range from 6 to 12.

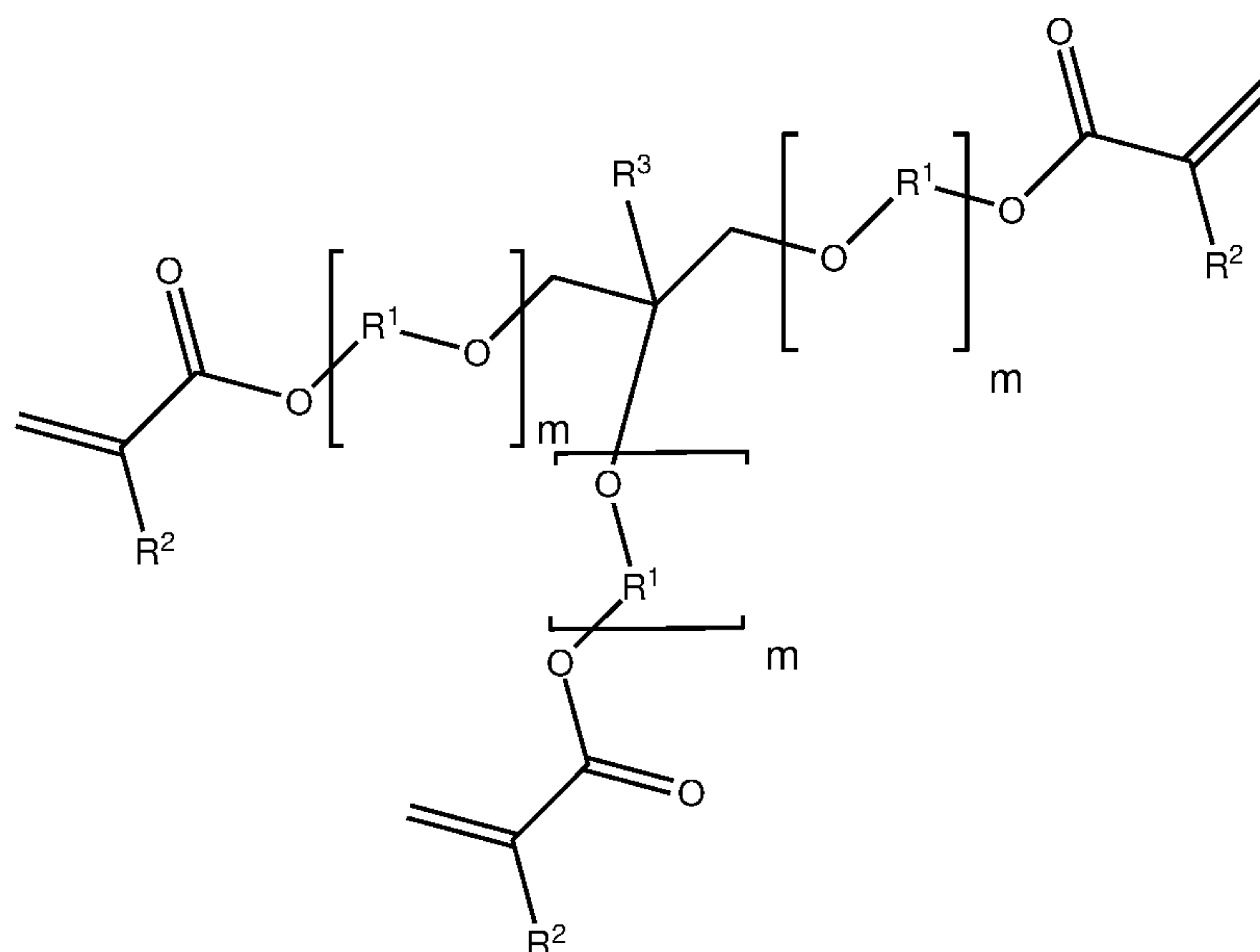
The fraction of the ether segments $-[O-R^1]_m$ present in the structural units of the formula (I) of component (a) is in total at least 35 wt%, more preferably at least 38 wt%, very preferably at least 40 wt%, more preferably still at least 42 wt%, more particularly at least 45 wt%, based in each case on the total weight of component (a).

Component (a) preferably has a molecular weight (M_n) in the range from 300 to 2000 g/mol, more preferably from 350 to 1500 g/mol, more particularly from 400 to 1000 g/mol.

Particularly preferred for use as component (a) is at least one compound of the general formula (IVa) and/or (IVb),



(IVa),



(IVb),

in which, in each case independently of one another,

5 R¹ and R² and also m have the definitions given above in connection with the structural units (I), including the preferred embodiments stated above, and

10 R³ is H, C₁-C₈ alkyl, OH or O-C₁₋₈ alkyl, more preferably is C₁-C₄ alkyl, OH or O-C₁₋₄ alkyl, and very preferably is C₁-C₄ alkyl or OH, or

15 R³ is the radical $-[O-R^1]_m-O-C(=O)-C(R^2)=CH_2$, in which R¹, R² and m have the definitions stated above in connection with the structural unit (I), including the preferred embodiments thereof stated above.

A particular preference is given to the use as component (a) of at least one compound of the general formula (IVa) in which

20 the radicals R¹ each independently of one another are a C₂-C₈ alkylene group,

25 the radicals R² each independently of one another are H or methyl,

the parameters m, in each case independently of one another, are an integral parameter in a range from 1 to 15, preferably in a range from 1 to 10, more preferably in a range from 1 to 8 or 2 to 8, very preferably in a range from 1 to 6 or 2 to 6, more particularly in a range from 1 to 4 or 2 to 4, but with the proviso that in at least one and preferably in all of the structural units of the formula (I), the parameter m is at least 2.

10 R³ is C₁-C₈ alkyl, OH or O-C₁₋₈ alkyl, more preferably C₁-C₄ alkyl, OH or O-C₁₋₄ alkyl, very preferably C₁-C₄ alkyl or OH.

Especially preferred for use as component (a) are (meth)acrylates of neopentyl glycol, trimethylolpropane, trimethylolethane or pentaerythritol with a total of 4-fold to 20-fold alkoxylation, or of 4-fold to 12-fold alkoxylation, such as ethoxylated, propoxylated or mixedly ethoxylated and propoxylated, and more particularly exclusively ethoxylated, neopentyl glycol, trimethylolpropane, trimethylolethane or pentaerythritol. The most preferred are corresponding (meth)acrylates deriving from correspondingly alkoxylation of trimethylolpropane. Products of these kinds are available commercially and are sold for example under the designations Sartomer® SR 499 and Sartomer® SR 502 and also Sartomer® SR 415 and Sartomer® SR 9035 and also Sartomer® SR 501. In the sense of the present invention, the term "(meth)acrylic" or "(meth)acrylate" embraces not only methacrylic but also acrylic and not only methacrylate but also acrylate, respectively.

30 Aside from the optional component (d), the coating composition (B1a) preferably contains no component which has only exactly one or only exactly two ethylenically unsaturated groups such as (meth)acrylic groups. Where (B1a) has no component (d), therefore, (B1a) preferably contains no component which has only precisely one or only precisely two ethylenically unsaturated groups such as (meth)acrylic groups.

Component (b) is an additive. The concept of the additive is

known to the skilled person, from Römpp Lexikon "Lacke und Druckfarben", Thieme Verlag, 1998, page 13, for example. A preferred component (b) used is at least one rheology additive. This term as well is known to the skilled person, from Römpp Lexikon "Lacke und Druckfarben", Thieme Verlag, 1998, page 497, for example. The terms "rheology additive", "rheological additive" and "rheology assistant" are interchangeable here. The additive used as component (b) is preferably selected from the group consisting of flow control agents, surface-active agents such as surfactants, wetting agents and dispersants, and also thickeners, thixotropic agents, plasticizers, lubricity and antiblocking additives, and mixtures thereof. These terms are likewise known to the skilled person, from Römpp Lexikon, "Lacke und Druckfarben", Thieme Verlag, 1998, for example. Flow control agents are components which by lowering the viscosity and/or surface tensions help coating materials to form films which flow out evenly. Wetting agents and dispersants are components which lower the surface tension or, generally, the interfacial tension. Lubricity and antiblocking additives are components which reduce mutual sticking (blocking).

Examples of commercially available additives are the products Efka® SL 3259, Byk® 377, Tego® Rad 2500, Tego® Rad 2800, Byk® 394, Byk-SILCLEAN 3710, Silixan® A250, Novec FC 4430 and Novec FC 4432.

Preferred for use as additive (b) is at least one poly(meth)acrylate and/or at least one siloxane such as at least one oligosiloxane and/or polysiloxane and/or at least one fluorine-containing polymer such as a fluorine-containing, preferably aliphatic polyester. Particularly preferred as component (b) are siloxanes. Especially preferred for use are silicone (meth)acrylates.

For the curing by means of (N)IR- and/or UV light, the coating composition (B1a) comprises at least one photoinitiator as component (c). This photoinitiator can be broken down, by light of the irradiated wavelength, into radicals, which are able in

turn to initiate a radical polymerization. In the case of curing with electronic radiation, conversely, there is no need for the presence of such photoinitiators. The coating composition (B1a) preferably includes at least one photoinitiator as component (c) which can be broken down, by light of the irradiated wavelength, into radicals which are able in turn to initiate a radical polymerization.

Photoinitiators such as UV photoinitiators are known to the skilled person. Examples of those contemplated include phosphine oxides, benzophenones, α -hydroxyalkyl aryl ketones, thioxanthenes, anthraquinones, acetophenones, benzoin and benzoin ethers, ketals, imidazoles or phenylglyoxylic acids and mixtures thereof.

Phosphine oxides are, for example, monoacyl- or bisacylphosphine oxides, as for example 2,4,6-trimethylbenzoyldiphenylphosphine oxide, ethyl 2,4,6-trimethylbenzoylphenylphosphinate or bis(2,6-dimethoxybenzoyl)-2,4,4-trimethylpentylphosphine oxide. Benzophenones are, for example, benzophenone, 4-aminobenzophenone, 4,4'-bis(dimethylamino)benzophenone, 4-phenylbenzophenone, 4-chlorobenzophenone, Michler's ketone, 4-methoxybenzophenone, 2,4,6-trimethylbenzophenone, 4-methylbenzophenone, 2,4-dimethylbenzophenone, 4-isopropylbenzophenone, 2-chlorobenzophenone, 2,2'-dichlorobenzophenone, 4-methoxybenzophenone, 4-propoxybenzophenone or 4-butoxybenzophenone; α -hydroxyalkyl aryl ketones are, for example, 1-benzoylcyclohexan-1-ol (1-hydroxycyclohexyl phenyl ketone), 2-hydroxy-2,2-dimethylacetophenone, (2-hydroxy-2-methyl-1-phenylpropan-1-one), 1-hydroxyacetophenone, 1-[4-(2-hydroxyethoxy)phenyl]-2-hydroxy-2-methyl-1-propan-1-one or a polymer containing in copolymerized form 2-hydroxy-2-methyl-1-(4-isopropen-2-ylphenyl)propan-1-one. Xanthenes and thioxanthenes are, for example, 10-thioxanthenone, thioxanthen-9-one, xanthen-9-one, 2,4-dimethylthioxanthone, 2,4-diethylthioxanthone, 2,4-diisopropylthioxanthone, 2,4-dichlorothioxanthone or chloroxanthenone; anthraquinones are, for example, β -

methylantraquinone, tert-butylantraquinone,
 anthraquinonecarboxylic esters, benz[de]anthracen-7-one,
 benz[a]anthracene-7,12-dione, 2-methylantraquinone, 2-
 ethylantraquinone, 2-tert-butylantraquinone, 1-
 5 chloroanthraquinon or 2-amylantraquinone. Acetophenones are,
 for example, acetophenone, acetonaphthoquinone, valerophenone,
 hexanophenone, α -phenylbutyrophenone, p-
 morpholinopropiophenone, dibenzosuberone, 4-
 morpholinobenzophenone, p-diacetylbenzene,
 10 4'-methoxyacetophenone, α -tetralone, 9-acetylphenanthrene, 2-
 acetylphenanthrene, 3-acetylphenanthrene, 3-acetylintole, 9-
 fluorenone, 1-indanone, 1,3,4-triacetylbenzene, 1-
 acetonaphthone, 2-acetonaphthone, 2,2-dimethoxy-2-
 phenylacetophenone, 2,2-diethoxy-2-phenylacetophenone, 1,1-
 15 dichloroacetophenone, 1-hydroxyacetophenone, 2,2-
 diethoxyacetophenone, 2-methyl-1-[4-(methylthio)phenyl]-2-
 morpholinopropan-1-one, 2,2-dimethoxy-1,2-diphenylethan-2-one
 or 2-benzyl-2-dimethylamino-1-(4-morpholinophenyl)-butan-1-
 one. Benzoin and benzoin ethers are, for example, 4-
 20 morpholinodeoxybenzoin, benzoin, benzoin isobutyl ether,
 benzoin tetrahydropyranyl ether, benzoin methyl ether, benzoin
 ethyl ether, benzoin butyl ether, benzoin isopropyl ether or 7H-
 benzoin methyl ether. Ketals are, for example, acetophenone
 dimethyl ketal, 2,2-diethoxyacetophenone, or benzil ketals, such
 25 as benzil dimethyl ketal. Photoinitiators which can also be used
 are, for example, benzaldehyde, methyl ethyl ketone, 1-
 naphthaldehyde, triphenylphosphine, tri-o-tolylphosphine or
 2,3-butanedione. Typical mixtures comprise, for example, 2-
 hydroxy-2-methyl-1-phenylpropan-2-one and 1-hydroxycyclohexyl
 30 phenyl ketone, bis(2,6-dimethoxybenzoyl)-2,4,4-trimethylpentyl-
 phosphine oxide and 2-hydroxy-2-methyl-1-phenylpropan-1-one,
 benzophenone and 1-hydroxycyclohexylphenyl ketone, bis(2,6-
 dimethoxybenzoyl)-2,4,4-trimethylpentylphosphine oxide and 1-
 hydroxycyclohexyl phenyl ketone, 2,4,6-trimethylbenzoyl-
 35 diphenylphosphine oxide and 2-hydroxy-2-methyl-1-phenylpropan-
 1-one, 2,4,6-trimethylbenzophenone and 4-methylbenzophenone or
 2,4,6-trimethylbenzophenone and 4-methylbenzophenone and 2,4,6-
 trimethylbenzoyldiphenylphosphine oxide.

Preferred among these photoinitiators are 2,4,6-trimethylbenzoyldiphenylphosphine oxide, ethyl 2,4,6-trimethylbenzoylphenylphosphinate, bis(2,4,6-trimethylbenzoyl)phenylphosphine oxide, benzophenone, 1-benzoylcyclohexan-1-ol, 2-hydroxy-2,2-dimethylacetophenone and 2,2-dimethoxy-2-phenylacetophenone. Preferably, therefore, at least one such photoinitiator is used as component (c). Component (c) is different from components (a), (b) and (d).
10 Commercially available photoinitiators are, for example, the products Irgacure® 184, Irgacure® 500, Irgacure® TPO, Irgacure® TPO-L and Lucirin® TPO and also Darocure® 1173 from BASF SE.

As mentioned above, the use of the at least one component (d) is only optional. Component (d) has at least one, preferably terminal, carbon double bond. This is preferably a (meth)acrylic group. Component (d) preferably has one or two ethylenically unsaturated groups such as, for example, one or two or three or else more (meth)acrylic groups. It is also possible for two or
20 more different components (d) to be used.

Examples of component (d) are mono-, di-, and/or tri-functional (meth)acrylic esters such as ethylene glycol di(meth)acrylate, 1,2-propanediol di(meth)acrylate, 1,3-propanediol di(meth)acrylate, 1,4-butanediol di(meth)acrylate, 1,3-butanediol di(meth)acrylate, 1,5-pentanediol di(meth)acrylate, 1,6-hexanediol di(meth)acrylate, 1,8-octanediol di(meth)acrylate, neopentyl glycol di(meth)acrylate, 1,1-, 1,2-, 1,3- and 1,4-cyclohexanedimethanol di(meth)acrylate, 1,2-,
30 1,3- or 1,4-cyclohexanediol di(meth)acrylate, tricyclodecanedimethanol di(meth)acrylate, trimethylolpropane tri(meth)acrylate, ditrimethylolpropane penta- or hexa(meth)acrylate, pentaerythritol tri- or tetra(meth)acrylate, glyceryl di- or tri(meth)acrylate, and also
35 di- and poly(meth)acrylates of sugar alcohols, as for example of sorbitol mannitol, diglycerol, threitol, erythritol, adonitol (ribitol), arabitol (lyxitol), xylitol, dulcitol (galactitol), maltitol or isomalt, 2-phenoxyethyl (meth)acrylate,

ethyldiglycol (meth)acrylate, 4-tert-butylcyclohexyl (meth)acrylate, trimethylolpropane formal mono(meth)acrylate, isobornyl (meth)acrylate, tetrahydrofurfuryl (meth)acrylate, 2-(2-ethoxyethoxy)ethyl (meth)acrylate and also lauryl, stearyl, isodecyl, octyl and decyl (meth)acrylate, esters of α,β -ethylenically unsaturated carboxylic acids, preferably of (meth)acrylic acid, with alcohols having 1 to 20 carbon atoms, preferably optionally hydroxy-substituted alkanols having 1 to 20 carbon atoms, e.g., methyl (meth)acrylic acid ester, ethyl (meth)acrylic acid ester, n-butyl (meth)acrylic acid ester, 2-ethylhexyl (meth)acrylic acid ester, 2-hydroxyethyl (meth)acrylate, 2-hydroxypropyl (meth)acrylate or 4-hydroxybutyl (meth)acrylate.

Especially preferred components (d) are 1,4-butanediol di(meth)acrylate and 1,6-hexanediol di(meth)acrylate and also tricyclodecanedimethanol di(meth)acrylate.

As component (d) it is also possible, additionally or alternatively, to use at least one polyester, polyether, carbonate, epoxide, poly (meth)acrylate and/or urethane (meth)acrylate, and/or unsaturated polyester resin.

Urethane (meth)acrylates are obtainable, for example, by reaction of polyisocyanates with hydroxyalkyl (meth)acrylates and optionally chain extenders such as diols, polyols, diamines, polyamines or dithiols or polythiols. Urethane (meth)acrylates dispersible in water without adding emulsifiers additionally contain ionic and/or nonionic hydrophilic groups, which are introduced into the urethane through synthesis components such as hydroxycarboxylic acids, for example. Such urethane (meth)acrylates contain essentially the following as synthesis components:

(a) at least one organic aliphatic, aromatic or cycloaliphatic di- or polyisocyanate, as for example at least one of the polyisocyanates described above in connection with the two-component coating materials,

(b) at least one compound having at least one isocyanate-reactive group, preferably one of the hydroxyl-bearing monomers described above in connection with the polyacrylate polyols, and
5 at least one radically polymerizable unsaturated group, and

(c) optionally at least one compound having at least two isocyanate-reactive groups, as for example one of the polyhydric alcohols described above in connection with the polyesterols.

10

The urethane (meth)acrylates preferably have a number-average molar weight M_n of 200 to 20 000, more particularly of 500 to 10 000, very preferably 600 to 3000 g/mol (determined by gel permeation chromatography with tetrahydrofuran and polystyrene
15 as standard). The urethane (meth)acrylates contain preferably from 1 to 5, more preferably from 2 to 4 mol of (meth)acrylic groups per 1000 g of urethane (meth)acrylate.

Epoxide (meth)acrylates are obtainable by reaction of epoxides
20 with (meth)acrylic acid. Examples of epoxides contemplated include epoxidized olefins, aromatic glycidyl ethers or aliphatic glycidyl ethers, preferably those of aromatic or aliphatic glycidyl ethers. Examples of possible epoxidized olefins include ethylene oxide, propylene oxide, isobutylene
25 oxide, 1-butene oxide, 2-butene oxide, vinyloxirane, styrene oxide or epichlorohydrin; ethylene oxide, propylene oxide, isobutylene oxide, vinyloxirane, styrene oxide or epichlorohydrin are preferred, ethylene oxide, propylene oxide or epichlorohydrin are particularly preferred, and ethylene
30 oxide and epichlorohydrin are especially preferred. Aromatic glycidyl ethers are, for example, bisphenol A diglycidyl ether, bisphenol F diglycidyl ether, bisphenol B diglycidyl ether, bisphenol S diglycidyl ether, hydroquinone diglycidyl ether, alkylation products of phenol/dicyclopentadiene, e.g., 2,5-
35 bis[(2,3-epoxypropoxy)phenyl]octahydro-4,7-methano-5H-indene, tris[4-(2,3-epoxypropoxy)phenyl]methane isomers, phenol-based epoxy novolacs and cresol-based epoxy novolacs. Aliphatic glycidyl ethers are, for example, 1,4-butanediol diglycidyl

ether, 1,6-hexanedioldiglycidyl ether, trimethylolpropane triglycidyl ether, pentaerythritol tetraglycidyl ether, 1,1,2,2-tetrakis[4-(2,3-epoxypropoxy)phenyl]ethane, diglycidyl ethers of polypropylene glycol (5 α,ω -bis(2,3-epoxypropoxy)poly(oxypropylene) (and of hydrogenated bisphenol A (2,2-bis[4-(2,3-epoxypropoxy)cyclohexyl]propane)). The epoxide (meth)acrylates preferably have a number-average molar weight M_n of 200 to 20 000, more preferably of 200 to 10 000 g/mol and very 10 preferably of 250 to 3000 g/mol; the amount of (meth)acrylic groups is preferably 1 to 5, more preferably 2 to 4, per 1000 g of epoxide (meth)acrylate (determined by gel permeation chromatography with polystyrene as standard and tetrahydrofuran as eluent).

15 (Meth)acrylated poly (meth)acrylates are the corresponding esters of α,β -ethylenically unsaturated carboxylic acids, preferably of (meth)acrylic acid, more preferably of acrylic acid, with polyacrylate polyols, obtainable by esterifying 20 poly(meth)acrylate polyols with (meth)acrylic acid. The polyacrylate polyols may for example be those as described above in connection with the two-component coating materials.

Carbonate (meth)acrylates are available with various 25 functionalities. The number-average molecular weight M_n of the carbonate (meth)acrylates is preferably less than 3000 g/mol, more preferably less than 1500 g/mol, very preferably less than 800 g/mol (determined by gel permeation chromatography with polystyrene as standard and tetrahydrofuran solvent). The 30 carbonate (meth)acrylates are obtainable in a simple way by transesterification of carbonic esters with polyhydric, preferably dihydric, alcohols (diols, e.g., hexanediol) and subsequent esterification of the free OH groups with (meth)acrylic acid or else transesterification with 35 (meth)acrylic esters, as described for example in EP 0 092 269 A1. They are also obtainable by reaction of phosgene, urea derivatives with polyhydric alcohols, dihydric alcohols for example. Also conceivable are meth(acrylates) of

polycarbonate polyols, such as the reaction product of one of the stated diols or polyols and a carbonic ester and also a hydroxyl-containing (meth)acrylate. Examples of suitable carbonic esters are ethylene, 1,2- or 1,3-propylene carbonate, 5 dimethyl, diethyl or dibutyl carbonate. Examples of suitable hydroxyl-containing (meth)acrylates are 2-hydroxyethyl (meth)acrylate, 2- or 3-hydroxypropyl (meth)acrylate, 1,4-butandiol mono(meth)acrylate, neopentyl glycol mono(meth)acrylate, glyceryl mono- and di(meth)acrylate, 10 trimethylolpropane mono- and di(meth)acrylate and also pentaerythritol mono-, di- and tri(meth)acrylate. With preference the carbonate (meth)acrylates are aliphatic carbonate (meth)acrylates.

15 Unsaturated polyester resins are preferably synthesized from the following components:

(a1) maleic acid or derivatives thereof,

20 (a2) at least one cyclic dicarboxylic acid or derivatives thereof,

(a3) at least one aliphatic or cycloaliphatic diol.

25 Derivatives here refer preferably to

- the relevant anhydrides in monomeric or else polymeric form,

30 - monoalkyl or dialkyl esters, preferably mono- or di-C₁-C₄ alkyl esters, more preferably monomethyl or dimethyl esters or the corresponding monoethyl or diethyl esters,

- additionally, monovinyl and divinyl esters, and also

35

- mixed esters, preferably mixed esters with different C₁-C₄ alkyl components, more preferably mixed methyl ethyl esters.

If (B1a) includes a component (d), that component is preferably at least one urethane (meth)acrylate.

The coating composition (B1a) may comprise at least one further
5 component (e), different from the components (a) to (d), such
as, for example, fillers, pigments, thermally activatable
initiators such as, for example, potassium peroxodisulfate,
dibenzoyl peroxide, cyclohexanone peroxide,
azobisisobutyronitrile, cyclohexylsulfonyl acetyl peroxide,
10 diisopropyl percarbonate, tert-butyl peroxoate or
benzopinacol, di-tert-butyl peroxide, cumene hydroperoxide,
dicumyl peroxide, tert-butyl perbenzoate, silylated pinacols,
hydroxyl-containing amine N-oxides, such as 2,2,6,6-
tetramethylpiperidine-N-oxyl and 4-hydroxy-2,2,6,6-
15 tetramethylpiperidine-N-oxyl, and organic solvents, and also
stabilizers. Preferably, however, there are no organic solvents
included in (B1a). Component (e) may be present in an amount in
a range from 0 to 15 wt%, preferably in a range from 0 to 12 wt%,
more preferably in a range from 0 to 10 wt% in (B1a), based in
20 each case on the total weight of the coating composition (B1a).

The solids content of the coating composition (B1a) is
preferably ≥ 80 wt%, more preferably ≥ 90 wt%, very preferably
 ≥ 95 wt%, more particularly ≥ 98 or ≥ 99 wt%, most preferably
25 100 wt%, based in each case on the total weight of the coating
composition (B1a). The solids content here is determined by the
method described below.

The coating composition (B1a) preferably contains no thiols, and
30 especially no trimethylolpropane tris(3-mercaptopropionate).

The double bond conversion of the at least partially cured
coating (B1) obtained from (B1a) is preferably at least 70%,
more preferably at least 75%, more preferably still at least
35 80%, very preferably at least 85%, more particularly at least
90%.

Coating composition (B2a)

Any kind of coating composition may be employed as coating composition (B2a) in step (1) of the method of the invention. The coating composition (B2a) may be a physically drying, thermally curable, chemically curable and/or radiation-curable coating composition (B2a). With preference the coating composition (B2a) is a chemically curable, a thermally curable and/or radiation-curable coating composition, more preferably a radiation-curable coating composition. Accordingly, the at least partial curing as per step (3) takes place preferably by means of radiation curing. The coating composition (B2a) may be identical to the coating composition (B1a). Preferably, however, (B2a) is different from (B1a). (B2a) is preferably constructed from the alike, but not the same, components (a) to (e) also used in the preparation of (B1a), although the quantity provisos relating to (B1a) do not have to apply to (B2a).

Physical drying here refers preferably to the simple evaporation of solvent(s) to form the coating (B2). Thermal curing here preferably entails a curing mechanism which is attributable to a temperature above room temperature ($> 23^{\circ}\text{C}$). This may be, for example, the formation of radicals or ions, preferably radicals from an initiator which breaks down at the elevated temperatures and so initiates a radical or ionic polymerization. Examples of such thermally activatable initiators are those which have a half-life at 80°C of less than 100 hours. Chemical curing refers preferably to the reaction of at least two different and mutually complementary reactive functional groups, in the manner, for example, of a polycondensation such as a reaction of an -OH group with a -COOH group, or of a polyaddition (reaction of an NCO group with an -OH or amino group).

If the coating composition (B2a) is a physically drying, thermally curable and/or chemically curable coating composition, it is prepared using, as binder, at least one customary polymer known to the skilled person. This binder then preferably has crosslinkable functional groups. Any customary crosslinkable functional group known to the skilled person is suitable in this

context. More particularly the crosslinkable functional groups are selected from the group consisting of hydroxyl groups, amino groups, carboxylic acid groups, isocyanates, polyisocyanates and epoxides. The polymers are preferably curable or crosslinkable
5 exothermically or endothermically, preferably in a temperature range from -20°C up to 250°C, or from 18°C to 200°C. Especially suitable as polymers are at least one polymer selected from the group consisting of polyurethanes, polyethers, polyesters, polyamides, polyureas, polyvinyl chlorides, polystyrenes,
10 polycarbonates, poly (meth)acrylates, epoxy resins, phenol-formaldehyde resins, melamine-formaldehyde resins. These polymers may in particular be OH-functional. In that case they may be subsumed by the general term "polyols". Such polyols may for example be polyacrylate polyols, polyester polyols,
15 polyether polyols, polyurethane polyols, polyurea polyols, polyester-polyacrylate polyols, polyester-polyurethane polyols, polyurethane-polyacrylate polyols, polyurethane-modified alkyd resins, fatty acid-modified polyester-polyurethane polyols, and also mixtures of the stated polyols. Preferred are polyacrylate
20 polyols, polyester polyols and polyether polyols.

It is possible here to use at least one polymer which is cured with participation of isocyanate and/or oligomerized isocyanate groups, very preferably at least one corresponding polyurethane
25 and/or at least one corresponding polyurea (e.g., what are called "polyaspartic binders"). Polyaspartic binders are components which are converted from reaction of amino-functional compounds, especially secondary amines, with isocyanates. If at least one polyurethane is used, then those suitable especially
30 are polyurethane-based resins which are preparable by a polyaddition reaction between hydroxyl-containing components such as polyols and at least one polyisocyanate (aromatic and aliphatic isocyanates, di-, tri- and/or polyisocyanates). Customarily here a stoichiometric conversion of the OH groups
35 in the polyols with the NCO groups in the polyisocyanates is required. However, the stoichiometric ratio to be used can also be varied, since the polyisocyanate can be added to the polyol component in amounts such that there may be an "over

crosslinking" or an "under crosslinking". If epoxy resins are used, i.e. epoxide-based resins, then those suitable are preferably epoxide-based resins which are prepared from glycidyl ethers which have terminal epoxide groups and, within the molecule, hydroxyl groups as functional groups. These are preferably reaction products of bisphenol A and epichlorohydrin and/or of bisphenol F with epichlorohydrin, and mixtures thereof, which are also used in the presence of reactive diluents. The curing or crosslinking of such epoxide-based resins is accomplished customarily by a polymerization of the epoxide groups of the epoxide ring, by a polyaddition reaction in the form of an addition reaction of other reactive compounds, as hardeners, in stoichiometric amounts with the epoxide groups, in which case, accordingly, the presence of one active hydrogen equivalent per epoxide group is required (i.e., one H-active equivalent is needed for curing per epoxide equivalent), or by a polycondensation via the epoxide groups and the hydroxyl groups. Examples of suitable hardeners are polyamines, especially (hetero)aliphatic, (hetero)aromatic and (hetero)cycloaliphatic polyamines, polyamidoamines, polyaminoamides, and also polycarboxylic acids and their anhydrides.

The concept of "radiation curing" has already been described above in connection with the coating composition (B1a). The coating composition (B2a) may be cured by use of a radiation source, preferably by using UV radiation. Preferably, therefore, (B2a) is a UV radiation-curing coating composition.

(B2a) preferably therefore has unsaturated carbon double bonds, more preferably (meth)acrylic groups. For this purpose, the coating composition (B2) may comprise any of the components identified above in connection with (B1a) and subsumable under the components (a) and (d) of (B1a), such as, in particular, polyester, polyether, carbonate, epoxide, poly(meth)acrylate and/or urethane (meth)acrylates and/or at least one unsaturated polyester resin and/or mono-, di- and/or tri-functional (meth)acrylic esters.

On curing by means of (N)IR and/or UV light, the coating composition (B2a) preferably comprises at least one photoinitiator which is able to be broken down into radicals by light of the irradiated wavelength, these radicals then being able to initiate a radical polymerization. In the case of curing with electronic radiation, in contrast, the presence of such photoinitiators is not necessary. As photoinitiators it is possible to use the same components in the same quantities as stated above in connection with component (c) of the coating composition (B1a).

The coating composition (B2a) may comprise at least one further additive, moreover. In that case it is possible to use the same components in the same amounts as identified above in connection with the components (b) and (e) of the coating composition (B1a).

The coating composition used as coating composition (B2a) is more preferably one having (meth)acrylic groups. With preference this coating composition (B2a) comprises at least one urethane (meth)acrylate. Preferably, moreover, it includes at least one photoinitiator.

Composite (F1B1) of the invention

A further subject of the present invention is a composite (F1B1) which is composed of a substrate (F1) and of an at least partially embossed and at least partially cured coating (B1), and which is producible by at least partially curing a coating composition (B1a), applied to at least a part of a surface of the substrate (F1) and at least partially embossed, by radiation curing, where the coating composition (B1a) is a radiation-curable coating composition which comprises

at least a component (a) in an amount in a range from 40 to 95 wt%,

at least an additive as component (b) in an amount in a range

from 0.01 to 5 wt%,

at least a photoinitiator as component (c) in an amount in a range from 0.01 to 15 wt%, and

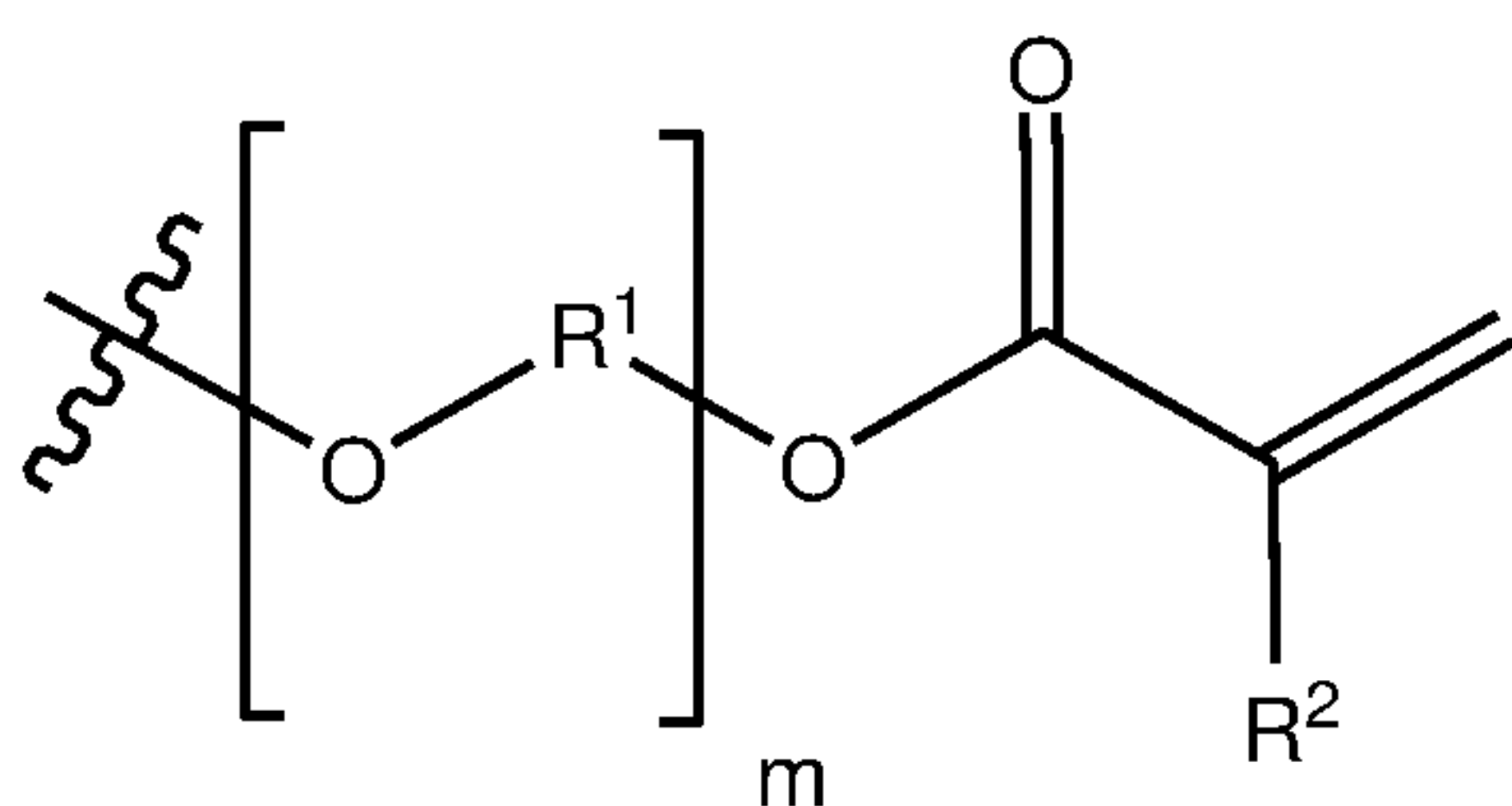
5

at least a component (d), comprising at least one carbon double bond, in an amount in a range from 0 to 45 wt%,

where (i) the components (a), (b), (c), and (d) are each
 10 different from one another, (ii) the stated amounts of the components (a), (b), (c), and (d) are each based on the total weight of the coating composition (B1a), and (iii) the amounts of all components present in the coating composition (B1a) add up to 100 wt%,

15

and where component (a) comprises at least three structural units, each different from one another or at least partially identical, of the formula (I)



20 (I),

in which

the radicals R^1 in each case independently of one another are a
 25 $\text{C}_2\text{-C}_8$ alkylene group,

the radicals R^2 in each case independently of one another are H or methyl, and

30 the parameters m each independently of one another are an integral parameter in a range from 1 to 15, but with the proviso that the parameter m is at least 2 in at least one of the structural units of the formula (I) within the component (a),

where the number of ether groups of the general formula " $-O-R^1-$ " within the component a) is in a range from 4 to 18.

All preferred embodiments described hereinabove in connection with the method of the invention, especially in connection with the coating composition (B1a) used therein and with the substrate (F1) and also of the coating (B1), are also preferred embodiments in relation to the composite (F1B1) of the invention.

The composite (F1B1) of the invention is obtainable preferably by implementation of the above-described method steps (5) to (8) of the method of the invention. The substrate (F1) is preferably a film web, more preferably a continuous film web.

Use

A further subject of the present invention is a use of the composite (F1B1) of the invention as embossing die (p2) of an embossing tool (P2) for transferring an embossed structure to at least a part of a surface of a coating composition (B2a) or to at least a part of a surface of a coating composition (B2a) which is at least partly applied on a substrate (F2), preferably of a substrate (F2) coated with a coating composition (B2a), preferably within the method of the invention.

All preferred embodiments described hereinabove in connection with the method of the invention and the composite (F1B1) of the invention are also preferred embodiments in relation to the aforementioned use of the composite (F1B1) of the invention.

The coating composition (B2a) here is preferably a radiation-curable coating composition.

Methods of determination

1. Determining the nonvolatile fraction

The nonvolatile fraction (the solids or solids content) is determined according to DIN EN ISO 3251 (date: June 2008). The method involves weighing out 1 g of sample into an aluminum tray that has been dried beforehand and drying the sample in a drying cabinet at 125°C for 60 minutes, cooling it in a desiccator, and then reweighing it. The residue, relative to the total amount of sample employed, corresponds to the nonvolatile fraction.

2. Determining the modeling accuracy

The modeling accuracy is determined by means of a commercial atomic force microscope (AFM) and using a commercial cantilever. By means of AFM it is possible accordingly to compare, for example, the surface topography of a defined lattice structure such as that of the embossing tool P1, having a depth of 140 nm, for example, and a period of 430 nm, for example, with the surface topography of a master film (B1F1) after embossing. In this case the embossing tool is deliberately damaged at a particular site in order to define a reference point. By means of this reference point it is possible to investigate and compare with one another the same regions of the reference and of the replication. The modeling accuracy defines how accurately a particular reference structure can be transferred, such as from the embossing tool P1 to a master film (B1F1), for example. If, for example, the investigated region of the embossing tool P1 features a lattice structure having a depth of 140 nm, then this reference depth is compared with the corresponding height of the structure determined on the master film (B1F1). The percentage change, corresponding here to the modeling accuracy, is defined as:

$$\Delta h = 100 * \left(1 - \frac{h_m}{h_r}\right)$$

Δh corresponds here to the percentage change, h_m to the height of the structure in the investigated region of the master film, and h_r to the corresponding depth of the structure of the investigated region of the embossing tool. This percentage change, in other words the modeling accuracy, is also referred

to as 'contraction'. The smaller the values of Δh , the better the modeling accuracy.

3. Determining the flow time

5

The flow time is determined in accordance with DIN EN ISO 2431 (date: March 2012). The method involves determining the flow time by means of a 4 mm flow cup (No. 4) at room temperature (20°C).

10

4. Determining the double bond conversion

The double bond conversion (DB conversion) is determined by ATR-IR spectroscopy after curing of the sample under investigation.

15

With the technique of ATR-IR spectroscopy, an IR spectrum is recorded at the site of contact of a round reflection crystal with the substrate. The contact site has a diameter of around 200 μm and the reflection crystal used is a germanium crystal.

20

Starting material used for calculating the double bond conversion comprises the corresponding wet specimens of the sample. The DB conversion is calculated by way of the decrease in intensity of the band at 810 cm^{-1} . A band used for standardization is an ester band at 1730 cm^{-1} . The percentage

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double bond conversion is calculated by the following formula:

$$DB - \text{conversion} = 100 * \left(1 - \frac{I_{810\text{cm}^{-1}}}{I_{\text{Ref}-810\text{cm}^{-1}}}\right)$$

Here, $I_{810\text{cm}^{-1}}$ is the standardized intensity at 810 cm^{-1} of the cured layer, and $I_{\text{Ref}-810\text{cm}^{-1}}$ is the standardized intensity at 810 cm^{-1} of the corresponding wet specimen. A double bond conversion $\geq 90\%$ is classed as sufficient.

30

5. Determining the adhesion

35

The adhesion is determined in accordance with DIN EN ISO 2409 (date: June 2013) by means of the cross-cut test. In this test,

in a duplicate determination, the adhesion of the coating layer under investigation to the substrate is examined. A cross-cut tester from Byk Gardner with a 2 mm cut spacing is used manually. Subsequently, Tesa tape 4651 is pressed onto the damaged area and peeled off to remove the delaminated regions. The assessment is made on the basis of characteristic values ranging from 0 (minimal delamination) to 5 (very high delamination). An average value of at least 3.5 is classed as sufficient.

10 6. Determining the success of replication

The success of replication is determined visually, with the percentage fraction of successfully replicated area being ascertained. The range here lies between 0% to 100% of successfully replicated area. If 100% of the area is not replicated, this means that a corresponding fraction of the area could not be removed from the embossing die, in other words that the coating B1 in the form of B1F1 remained partially adhering to the embossing tool P1, or that the coating B2 remained partially adhering to the master film B1F1.

Inventive and comparative examples

The inventive and comparative examples below serve to illustrate the invention, but should not be interpreted as imposing any restriction.

Unless otherwise indicated, the amounts in parts are parts by weight and amounts in percent are in each case percentages by weight.

1. Compounds and materials used

Hostaphan® GN - commercially available PET film with a layer thickness of 125 µm.

Laromer® UA 9033 (L UA 9033) - aliphatic urethane acrylate from BASF SE, employable as component (d)

Hexanediol diacrylate (HDDA) - employable as component (d)

5 Sartomer® 395 (SR 395) - isodecyl acrylate from Sartomer,
employable as component (d)

10 Sartomer® 502 (SR 502) - TMPTA (trimethylpropane triacrylate)
with 9-fold ethoxylation, from Sartomer, employable as component
(a)

Sartomer® 499 (SR 499) - TMPTA (trimethylpropane triacrylate)
with 6-fold ethoxylation, from Sartomer, employable as component
(a)

15 Sartomer® 454 (SR 454) - TMPTA (trimethylpropane triacrylate)
with 3-fold ethoxylation, from Sartomer, employable as
comparative component (a)

20 TMPTA (trimethylpropane triacrylate) - employable as comparative
component (a)

GPTA (glyceryl propoxytriacrylate) - glyceryl triacrylate with
3-fold propoxylation, employable as comparative component (a)

25 Irgacure® 184 (I-184) - commercially available photoinitiator
from BASF SE, employable as component (c)

Irgacure® TPO-L (I-TPO-L) - commercially available
photoinitiator from BASF SE, employable as component (c)

30 Irgacure® TPO (I-TPO) - commercially available photoinitiator
from BASF SE, employable as component (c)

35 Tego® Rad 2500 (TR 2500) - lubricity and antiblocking additive
from Evonik (silicone acrylate), employable as component (b)

Byk-SILCLEAN 3710 (BS 3710) - surface additive from BYK Chemie
GmbH (polyether-modified polydimethylsiloxane with acrylic

functionality), employable as component (b)

2. Examples

5 2.1 *Production of coating compositions (B1a) and corresponding comparative coating compositions*

The coating compositions were produced in accordance with tables 1a and 1b below. Coating compositions E1a to E7a are inventive.
10 Coating compositions V1a to V5a are comparative coating compositions. The flow times ascertained at room temperature (20°C) are in the range from 26 to 172 s in the case of the production of E1a to E3a and V1a to V5a.

Table 1a:

<i>Coating composition</i>	<i>Component (a) or comparative component (a)</i>	<i>Component (b)</i>	<i>Component (d)</i>	<i>Component (c)</i>
E1a	SR 499 (65 parts)	TR 2500 (1 part)	L UA 9033 (13.5 parts) and HDDA (13.5 parts)	I-184 (3.5 parts) and I-TPO-L (3.5 parts)
E2a	SR 499 (92 parts)	TR 2500 (1 part)	-	I-184 (3.5 parts) and I-TPO-L (3.5 parts)
E3a	SR 502 (65 parts)	TR 2500 (1 part)	L UA 9033 (13.5 parts) and HDDA (13.5 parts)	I-184 (3.5 parts) and I-TPO (3.5 parts)
V1a	SR 499 (65 parts)	-	L UA 9033 (13.5 parts) and HDDA (13.5 parts)	I-184 (3.5 parts) and I-TPO-L (3.5 parts)
V2a	SR 454 (65 parts)	TR 2500 (1 part)	L UA 9033 (13.5 parts) and HDDA (13.5 parts)	I-184 (3.5 parts) and I-TPO (3.5 parts)

V3a	TMPTA (50 parts)	TR 2500 (1 part)	L UA 9033 (26 parts) and SR 395 (16 parts)	I-184 (3.5 parts) and I-TPO-L (3.5 parts)
V4a	GPTA (50 parts)	TR 2500 (1 part)	L UA 9033 (26 parts) and SR 395 (16 parts)	I-184 (3.5 parts) and I-TPO-L (3.5 parts)
V5a	SR 499 (32 parts)	TR 2500 (1 part)	L UA 9033 (30 parts) and HDDA (30 parts)	I-184 (3.5 parts) and I-TPO-L (3.5 parts)

Table 1b:

Coating composition	Component (a) or comparative component (a)	Component (b)	Component (d)	Component (c)
E4a	SR 499 (63 parts)	TR 2500 (0.5 part)	L UA 9033 (13.5 parts) and HDDA (13.5 parts)	I-184 (3.5 parts) and I-TPO (3.5 parts)
E5a	SR 499 (63 parts)	TR 2500 (1 part)	L UA 9033 (13.5 parts) and HDDA (13.5 parts)	I-184 (3.5 parts) and I-TPO (3.5 parts)

					parts)	
E6a	SR 499 (63 parts)	TR 2500 (2 parts)	L UA 9033 (13.5 parts) and HDDA (13.5 parts)	I-184 (3.5 parts) and I-TPO (3.5 parts)		
E7a	SR 499 (63 parts)	BS 3710 (1 part)	L UA 9033 (13.5 parts) and HDDA (13.5 parts)	I-184 (3.5 parts) and I-TPO (3.5 parts)		

2.2 Production of master films (B1F1) using E1a to E3a and V1a to V5a

A number of different master films are produced using a roll-to-plate embossing apparatus with a nickel embossing tool P1 bearing the desired positive structure. For this purpose, one each of the above-described coating compositions E1a to E3a and V1a to V5a is applied to P1, and a PET film (F1) is applied over it (Hostaphan® GN). The resulting stack of film and respective coating composition then runs through beneath a pressing roll and, still while the embossing apparatus is in contact with the coating composition of the respective stack, the coating compositions are at least partly cured by means of a UV-LED lamp. The lamp used in this case is a 365 nm, 6 W UV-LED lamp from Easytec (100% lamp power, 2 m/min, 2 passes). The at least partially cured coating together with film, with the negative structure by comparison with P1, is subsequently separated from the embossing apparatus, to give the structured film (master film). The master films are subsequently post-exposed with a UVA lamp (Panacol-Elosal UV F-900).

Furthermore, a master film is produced using a roll-to-roll embossing apparatus with a nickel embossing tool P1 bearing the desired positive structure. For this purpose, the above-described coating composition E1a is applied to a PET film (F1) (Hostaphan® GN) and guided over the embossing tool P1 with the aid of a pressing roll. Still while the embossing apparatus is in contact with the coating composition, the coating composition is at least partly cured by means of a UV-LED lamp. The lamp used in this case is a 365 nm, 6 W UV-LED lamp from Easytec (100% lamp power, 5 m/min). The at least partially cured coating together with film, with the negative structure by comparison with P1, is subsequently separated from the embossing apparatus, to give the structured film (master film). The master film is subsequently post-exposed with a UVA lamp (Panacol-Elosal UV F-900).

2.3 Production of master films (B1F1) using E4a to E7a

A number of different master films are produced using a nickel embossing tool P1 bearing the desired positive structure. For this purpose, one each of the above-described coating compositions E4a to E7a is applied to P1, and a PET film is applied over it (Hostaphan® GN). The resulting stack of film and respective coating composition is then pressed on with a rubber roller and, still while the embossing apparatus is in contact with the coating composition of the respective stack, the coating compositions are at least partly cured by means of a UV-LED lamp. The lamp used in this case is a 365 nm, 6 W UV-LED lamp from Easytec (100% lamp power, 2 m/min, 2 passes). The at least partially cured coating together with film, with the negative structure by comparison with P1, is subsequently separated from the embossing apparatus, to give the structured film (master film).

2.4 Master films produced

In the manner described in sections 2.2 and 2.3, various sets of master films are obtained (E1F1 to E7F1 and V1F1 to V5F1), additionally differing in their embossing according to the nature of the positive structure. In this case, embossing apparatuses of nickel with different positive structures were used, specifically with

- a nanostructure (lattice structure with a period of 430 nm and a depth of 140 nm; the respective coating composition is applied in layer thicknesses between 5-10 μm to the PET film employed),
- a microstructure A (two-dimensional triangle structure with a width and height of 33 μm and a space of 35 μm between the structures; the respective coating composition is applied in layer thicknesses between 20 μm to the PET film employed),
- a microstructure B (continuous two-dimensional triangle structure with a width of 43 μm and a height of 10 μm ; the

respective coating composition is applied in layer thicknesses of 20 μm to the PET film employed), or with

- a microstructure C (two-dimensional triangle structure with a height of 80 μm and a space of 115 μm between the structures; the respective coating composition is applied in layer thicknesses of 110 μm to the PET film employed).

The master films with the nanostructure are used for determining the modeling accuracy, the double bond conversions, and the adhesion. The master films with the microstructure A are used for determining the success of replication in the case of those master films produced using one of the coating compositions E1a to E3a and V1a to V5a (cf. Point 2.5 below) and also used as embossing die as described below under Point 2.6. The master films with the microstructure B are used for determining the success of replication in the case of those master films produced using one of the coating compositions E4a to E7a (cf. Point 2.5 below) and also used as embossing die as described below under Point 2.6. The master film with the microstructure C is used as embossing die as described below under Point 2.7. In order to produce this master film the coating composition E1a is used and a master film E1F1 with microstructure C is correspondingly obtained.

2.5 Investigations on the master films

Table 2 below summarizes the investigations conducted. The investigations were each conducted in accordance with the methods described above. The symbol "-" within the table denotes that the particular investigation was not carried out.

Tab. 2:

<i>Master film</i>	<i>DB conversion (%)</i>	<i>Adhesion</i>	<i>Success of replication (%)</i>	<i>Modeling accuracy (Δh, %)</i>
E1F1	92	3.5	100	4

E2F1	90	0.5	100	4
E3F1	95	2.5	–	4
V1F1	93	5	100	3
V2F1	85	1.5	85	2
V3F1	89	5	85	5
V4F1	92	5	100	4
V5F1	87	5	85	29
E4F1	–	–	100	–
E5F1	–	–	100	<1
E6F1	–	–	100	–
E7F1	–	–	100	<1

The data show that in the case of V2F1, V3F1 and V5F1 there is no attainment of sufficient DB conversion (DB conversion < 90). With too low a DB conversion, problems may occur in the embossing both of the coating composition (B1a) and also, later on, of the coating composition (B2a). The master films E1F1, E2F1 and E3F1, conversely, show DB conversions of at least 90%.

In the case of V1F1 and V4F1, the DB conversions are indeed > 90%, but the adhesion achieved with these master films, just as with V3F1 and V5F1 is inadequate (cross-cut test evaluated with a rating of 5). If adhesion of the master coating on the PET film is insufficient, problems may occur during embossing both of the coating composition (B1a) and also, later on, of the coating composition (B2a). The master films E1F1, E2F1 and E3F1, conversely, all exhibit good to sufficient adhesion properties.

The data additionally show that in the case of V2F1, V3F1 and V5F1, only values of 85% are obtained in the assessment of the success of replication, since 15% of the respective coating V2, V3 and V5 could not be removed from the embossing tool. Conversely, the investigated master films E1F1 and E2F1 exhibit a replication success of 100%.

Apart from V5F1, all of the master films investigated exhibit sufficient modeling accuracy, since very low contraction values are obtained consistently. Only in the case of V5F1 is the

contraction obtained 29%, which is unacceptable.

In summary it can be stated that only the master films E1F1, E2F1 and E3F1 furnish good results in respect of all of the properties investigated (DB conversion, adhesion, modeling accuracy, and success of replication).

2.6 Use of the master films as embossing die for producing embossed product films

10

The master films obtained respectively with the microstructure A or B are then each used as embossing die of an embossing tool. For this purpose, the master film is used in a roll-to-plate embossing apparatus. A coating composition (B2a) is applied with a wet layer thickness of 20 μm to the respective master film. Moreover, a PET film as substrate F2 (Hostaphan® GN) is contacted with the coating composition (B2a). The resulting stack of film and coating composition (B2a) then runs through beneath a pressing roll and, while the embossing device is still in contact with the coating composition of the respective stack, the coating composition (B2a) is at least partially cured by a UV-LED lamp. The lamp used in this case is a 365 nm, 6 W UV-LED lamp from Easytec (100% lamp power, 2 m/min, 2 passes). The at least partially cured coating B2 together with film F2 with the desired final embossed structure is subsequently parted from the embossing die, in other words from the particular master film used, of the embossing tool, and the structured product film (B2F2) is obtained.

30 The coating composition (B2a) employed is a commercial, radiation-curing coating composition which comprises at least one urethane acrylate and at least one photoinitiator and also commercial additives.

35 Table 3a below summarizes the results of the investigations of the success of replication performed on the resultant product films, taking account of the particular master film used for embossing. The symbol "-" within the table denotes that the

particular investigation was not carried out.

Tab. 3a: Success of replication of the embossed structure of the product film

5

<i>Master film used</i>	<i>Success of replication (%)</i>
E1F1	100
E2F1	100
E3F1	–
E4F1	100
E5F1	100
E6F1	100
E7F1	100
V1F1	42*
V2F1	100
V3F1	85
V4F1	100
V5F1	100

* = Average from two determinations

10 The data show that in the case where V1F1 and V3F1 were used as the embossing die, values of only <100% are obtained when assessing the success of replication, since in these cases 15% or 58% of the coating B2 could not be removed from the coatings V1 and V3 of the respective master films. Conversely, when using the investigated master films E1F1, E2F1 and E4F1 to E7F1 as
15 embossing die, a replication success of 100% of the coating B2 of the product film is achieved.

2.7 Further use of the master films as embossing die for producing embossed product films

20

The master film obtained with the microstructure C (E1F1) is used as embossing die. A coating composition (B2a) is applied with a wet layer thickness of 100 µm to the master film. Moreover, a PET film as substrate F2 (Hostaphan® GN) is contacted

with the coating composition (B2a) and pressed on. The resulting stack of film (F1), coating (B1, i.e. E1), coating composition (B2a) and film (F2) is cured at room temperature (23°C) for a period of 24 hours. The at least partially cured coating (B2) together with film (F2) with the desired final embossed structure is subsequently parted from the embossing die, in other words from the master film (E1F1) used with the microstructure C and the structured product film (B2F2) is thus obtained.

The coating composition (B2a) employed is a commercial, thermally curing two component epoxy resin (Epofix from Struers GmbH). The mixing ratio between component 1 and component 2 is 9:1. Component 1 comprises at least one bisphenol epichlorohydrin. Component 2 comprises at least one polyamine.

Table 3b below summarizes the results of the investigation of the success of replication performed on the resultant product film, taking account of the master film used for embossing.

Tab. 3b: Success of replication of the embossed structure of the product film

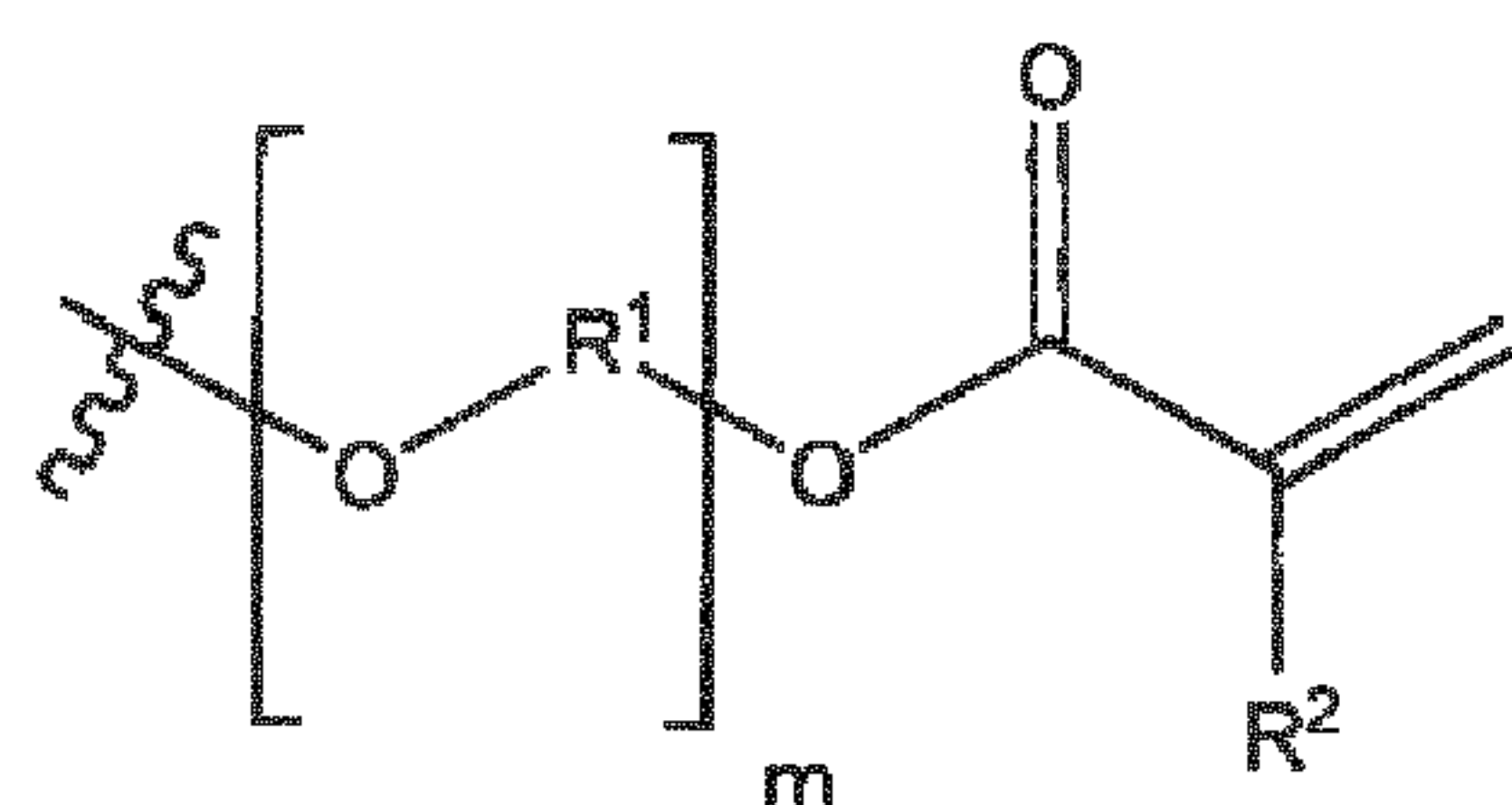
<i>Master film used</i>	<i>Success of replication (%)</i>
E1F1	100

With the use of the master film E1F1 as embossing die, a replication success of 100% of the coating B2 of the product film is achieved, even when a thermally curing coating composition is used as coating composition (B2a).

Patentkrav

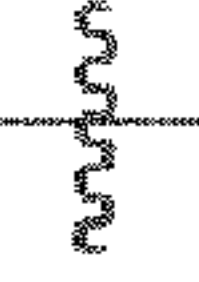
1. En fremgangsmåde til overførsel af en prægestruktur på i det mindste en del af en overflade på et andet belægningsmiddel
- 5 B2a, som omfatter i det mindste trinnene 1-i) og 2-i) eller 1-ii) og 2-ii) samt i det mindste trinnene 3) og valgfrit 4), nemlig
- 1-i) applikation af et andet belægningsmiddel B2a på i det mindste en del af en overflade på et andet substrat F2 og
- 10 2-i) i det mindste delvis prægning af det i det mindste delvist på overfladen af det andet substrat F2 applicerede andet belægningsmiddel B2a ved hjælp af i det mindste et andet prægeværktøj P2 med i det mindste en anden prægematrice p2, idet den anden prægematrice p2 omfatter en første forbindelse B1F1
- 15 af et første substrat F1 og en i det mindste delvist præget og i det mindste delvist hærdet første belægning B1, idet der efter den i det mindste delvise prægning opnås en anden forbindelse F2B2aB1F1,
- eller
- 20 1-ii) applikation af et andet belægningsmiddel B2a på i det mindste en del af en i det mindste delvist præget overflade på en som en anden prægematrice p2 i et andet prægeværktøj P2 anvendt første forbindelse B1F1 af et første substrat F1 og en i det mindste delvist præget og i det mindste delvist hærdet
- 25 første belægning B1, idet der opnås en tredje forbindelse B2aB1F1, og
- 2-ii) applikation af et andet substrat F2 på i det mindste en del af den ved hjælp af det andet belægningsmiddel B2a dannede overflade på den tredje forbindelse B2aB1F1, idet der opnås en
- 30 anden forbindelse F2B2aB1F1,
- og
- 3) i det mindset delvis hærkning af det andet belægningsmiddel B2a inden for den således opnåede anden forbindelse F2B2aB1F1, idet der opnås en fjerde forbindelse F2B2B1F1, idet det andet
- 35 belægningsmiddel B2a i hele varigheden af den i det mindste delvise hærkning er i kontakt med den som anden prægematrice p2 anvendte første delforbindelse B1F1 inden for den anden forbindelse F2B2aB1F1, og

4) i givet fald fjernelse af den femte forbindelse F2B2 inde i den fjerde forbindelse F2B2B1F1 fra den som anden prægematrice p2 anvendte første forbindelse B1F1, idet det til fremstillingen af den første belægning B1 på den som anden prægematrice p2 anvendte første forbindelse B1F1 anvendte første belægningsmiddel B1a er et strålehærdeligt belægningsmiddel, kendetegnet ved, at det første belægningsmiddel B1a indeholder i det mindste en første bestanddel a) i en mængde i et område fra 40 til 95 vægt-%, i det mindste et additiv som anden bestanddel b) i en mængde i et område fra 0,01 til 5 vægt-%, i det mindste en fotoinitiator som tredje bestanddel c) i en mængde i et område fra 0,01 til 15 vægt-%, og i det mindste en fjerde bestanddel d) med i det mindste en carbondobbeltbinding i en mængde i et område fra 0 til 45 vægt-%, idet i) bestanddelene a), b), c) og d) hver især er forskellige fra hinanden, ii) de anførte mængder af bestanddelene a), b), c) og d) hver især er baseret på den samlede vægt af det første belægningsmiddel B1a, og iii) mængderne af alle i det første belægningsmiddel B1a indeholdte bestanddele adderes til 100 vægt-%, og idet den første bestanddel a) har i det mindste tre hver især fra hinanden forskellige eller i det mindste delvist identiske strukturenheder med formel (I)



(I),

hvor grupperne R¹ hver især uafhængigt af hinanden står for en C₂-C₈-alkylengruppe, grupperne R² hver især uafhængigt af hinanden står for H eller methyl, og parametrene m hver især uafhængigt af hinanden står for en heltalsparameter i et område fra 1 til 15, dog på den betingelse

at parameteren m i i det mindste en af strukturenhederne med formel (I) i den første bestanddel a) er i det mindste 2, idet symbolet " " i denne forbindelse står for en binding af den pågældende gruppe til den overordnede struktur i bestanddel a).

5

2. Fremgangsmåde ifølge krav 1, kendetegnet ved, at det i forbindelse med det andet substrat F2 drejer sig om en fortrinsvis bevægende foliebane.

10 3. Fremgangsmåde ifølge krav 1 eller 2, kendetegnet ved, at der ved hjælp af trin 2-i) eller ved hjælp af trinnene 1-ii) og 2-ii) overføres mikro- og/eller nanostrukturer som prægestruktur på det andet belægningsmiddel B2a.

15 4. Fremgangsmåde ifølge et af de foregående krav, kendetegnet ved, at den i trin 2-i) og 1-ii) anvendte anden prægematrice p2 i det andet prægeværktøj P2 kan genanvendes og flere gange kan anvendes til at overføre i det mindste en prægestruktur, hvis trin 4) i fremgangsmåde gennemføres.

20

5. Fremgangsmåde ifølge et af de foregående krav, kendetegnet ved, at den i trin 2-i) og 1-ii) som anden prægematrice p2 anvendte første forbindelse B1F1 er en forbindelse af en foliebane som første substrat F1 og en herpå påført og i det
25 mindste delvist præget og i det mindste delvist hærdet første belægning B1.

6. Fremgangsmåde ifølge et af de foregående krav, kendetegnet ved, at

30 den i trin 2-i) som anden prægematrice p2 anvendte første forbindelse B1F1 under gennemførelse af trin 2-i) føres over en som andet prægeværktøj P2 fungerende første valse, og en sjette forbindelse F2B2a føres over en anden valse, som ligger over for den første valse og løber samme vej eller modsat denne, og
35 den i trin 1-ii) som anden prægematrice p2 anvendte første forbindelse B1F1 efter applikationen af det andet belægningsmiddel B2a på i det mindste en del af sin i det mindste delvist prægede overflade, idet der opnås den tredje forbindelse

B2aB1F1, under gennemførelse af trin 2-ii) føres over en som andet prægeværktøj P2 fungerende første valse, og det inden for trin 2-ii) anvendte andet substrat F2 føres over en anden valse, som ligger over for den første valse og løber modsat eller i
5 samme retning som denne.

7. Fremgangsmåde ifølge krav 6, kendetegnet ved, at den i det mindste delvise prægning ifølge trin 2-i) sker på højde med valespalten, som dannes ved hjælp af de to over for
10 hinanden liggende, modsat løbende eller i samme retning drejende valser, idet den i det mindste delvist prægede første belægning B1 i den første forbindelse B1F1 vender mod det andet belægningsmiddel B2a på den sjette forbindelse F2B2a, og den i det mindste delvise prægning ifølge trin 2-ii) sker på
15 højde med valespalten, som dannes ved hjælp af de to over for hinanden liggende, i modsat retning eller i samme retning drejende valser, idet det andet belægningsmiddel B2a i den tredje forbindelse B2aB1F1 vender mod det andet substrat F2

20 8. Fremgangsmåde ifølge et af de foregående krav, kendetegnet ved, at indholdet af faste legemer i det første belægningsmiddel B1a er ≥ 90 vægt-%, baseret på den samlede vægt af det første belægningsmiddel B1a.

25 9. Fremgangsmåde ifølge et af de foregående krav, kendetegnet ved, at parameteren m i hver af de i det mindste tre strukturenheder med formel (I) i den første bestanddel a) er i det mindste 2.

30 10. Fremgangsmåde ifølge et af de foregående krav, kendetegnet ved, at andelen af de i strukturenhederne med formel (I) indeholdte ethersegmenter $-[O-R^1]_m-$ i bestanddel a) er i det mindste 35 vægt-%, baseret på den samlede vægt af den første bestanddel a).

35

11. Fremgangsmåde ifølge et af de foregående krav, kendetegnet ved, at den som anden prægematrice p2 i det andet prægeværktøj P2 anvendte første forbindelse F1B1 af et første substrat F1 og

en i det mindste delvist præget og i det mindste delvist hærdet første belægning B1 i det mindste er opnåelig ved hjælp af trinnene 5) til 8), nemlig

5) applicering af det strålehærdelige første belægningsmiddel

5 Bla på i det mindste en del af en overflade på et første substrat F1,

6) i det mindste delvis prægning af det i det mindste delvist på overfladen af det første substrat F1 applicerede første belægningsmiddel Bla ved hjælp af i det mindste et første

10 prægeværktøj P1 med i det mindste en første prægematrice p1,

7) i det mindste delvis hærkning af det på i det mindste en del af overfladen på det første substrat F1 applicerede og i det mindste delvist prægede første belægningsmiddel Bla ved hjælp af strålehærkning, idet der opnås en første forbindelse F1B1 af

15 et første substrat F1 og i det mindste delvist præget og i det mindste delvist hærdet første belægning Bla, idet det første belægningsmiddel Bla under hele varigheden af den i det mindste delvise hærkning er i kontakt med den i det mindste ene første prægematrice p1 på det i det mindste ene første prægeværktøj P1,

20 og

8) fjernelse af den første forbindelse F1B1 fra det første prægeværktøj P1.

12. En første forbindelse F1B1 af et første substrat F1 og en
25 i det mindste delvist præget og i det mindste delvist hærdet første belægning B1, som kan fremstilles ved hjælp af i det mindste delvis hærkning af en på i det mindste en del af en overflade på det første substrat F1 appliceret og i det mindste delvist præget første belægningsmiddel Bla ved hjælp af
30 strålehærkning, idet det første belægningsmiddel Bla er et strålehærdeligt belægningsmiddel, kendetegnet ved, at det første belægningsmiddel Bla

indeholder i det mindste en første bestanddel a) i en mængde i et område fra 40 til 95 vægt-%,

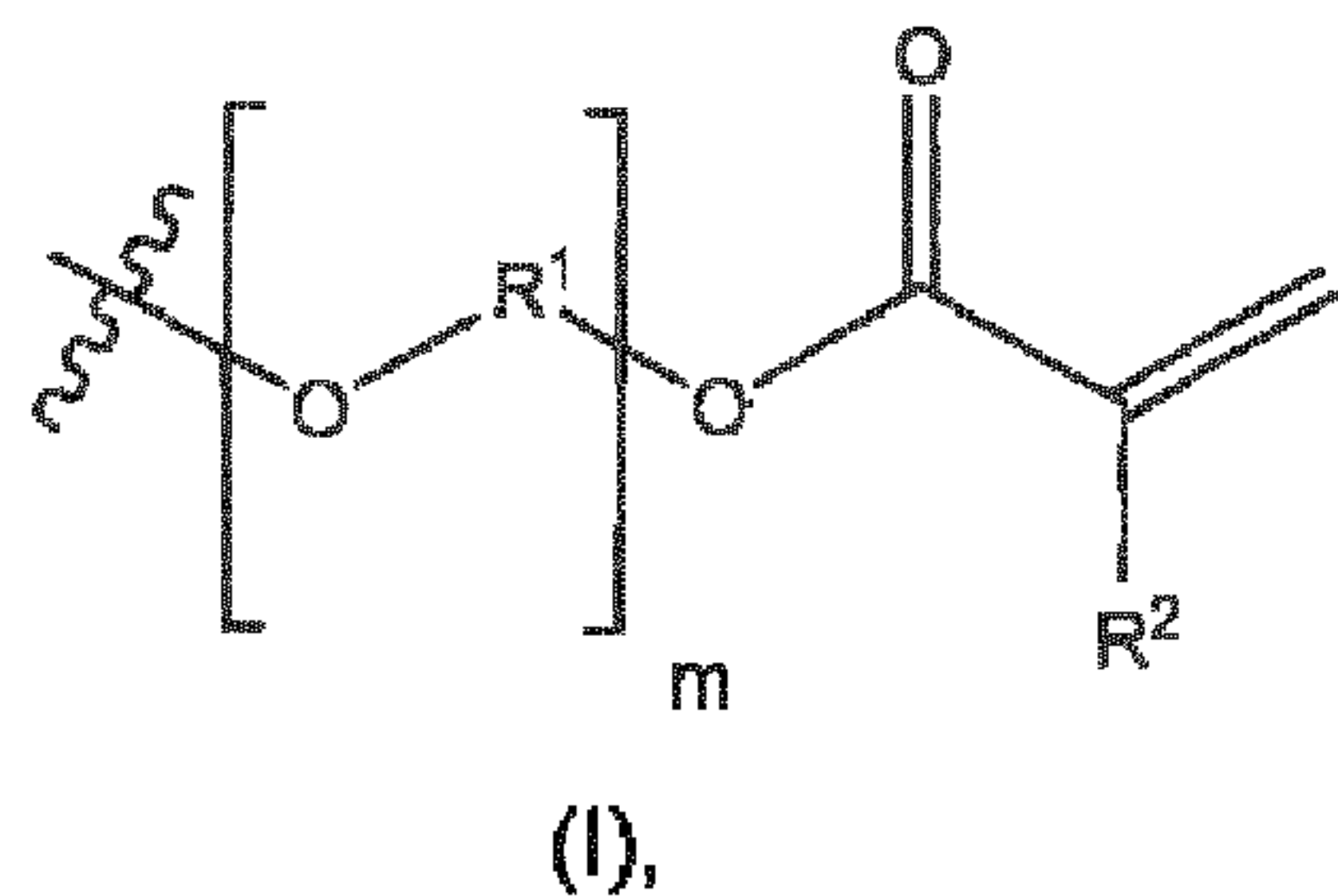
35 i det mindste et additiv som anden bestanddel b) i en mængde i et område fra 0,01 til 5 vægt-%,

i det mindste en fotoinitiator som tredje bestanddel c) i en mængde i et område fra 0,01 til 15 vægt-%, og

i det mindste en fjerde bestanddel d) med i det mindste en carbondobbeltbinding i en mængde i et område fra 0 til 45 vægt-%,

idet i) bestanddelene a), b), c) og d) hver især er forskellige fra hinanden, ii) de anførte mængder af bestanddelene a), b), c) og d) hver især er baseret på den samlede vægt af det første belægningsmiddel Bla, og iii) mængderne af alle i det første belægningsmiddel Bla indeholdte bestanddele adderes til 100 vægt-%,

og idet den første bestanddel a) har i det mindste tre hver især fra hinanden forskellige eller i det mindste delvist identiske strukturenheder med formel (I)

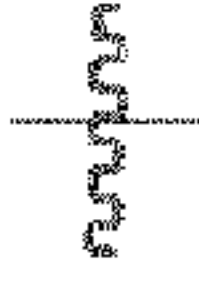


hvor

grupperne R^1 hver især uafhængigt af hinanden står for en C_2 - C_8 -alkylengruppe,

grupperne R^2 hver især uafhængigt af hinanden står for H eller methyl, og

parametrene m hver især uafhængigt af hinanden står for en heltalsparameter i et område fra 1 til 15, dog på den betingelse at parameteren m i den første bestanddel a) i i det mindste en af strukturenhederne med formel (I) er i det mindste 2,

idet symbolet "  " i denne forbindelse står for en binding af den pågældende gruppe til den overordnede struktur i bestanddel a), og

idet antallet af ethergrupper med den almene formel " $-O-R^1-$ " inden for bestanddel a) ligger i et område fra 4 til 18.

13. Den første forbindelse F1B1 ifølge krav 12, kendetegnet ved, at forbindelsen er opnåelig ved hjælp af gennemførelse af de i krav 11 beskrevne fremgangsmådetrin 5) til 8).

14. Den første forbindelse F1B1 ifølge krav 12 eller

13, kendetegnet ved, at det i forbindelse med det første substrat F1 drejer sig om en fortrinsvis bevægende foliebane.

15. Anvendelse af den første forbindelse F1B1 ifølge et af
5 kravene 12 til 14 som anden prægematrice p2 i et andet
prægeværktøj P2 til overførsel af en prægestruktur på i det
mindste en del af en overflade på et andet belægningsmiddel B2a
eller på i det mindste en del af en overflade på et andet
belægningsmiddel B2a, som i det mindste delvist er appliceret
10 på et andet substrat F2.

Fig. 1

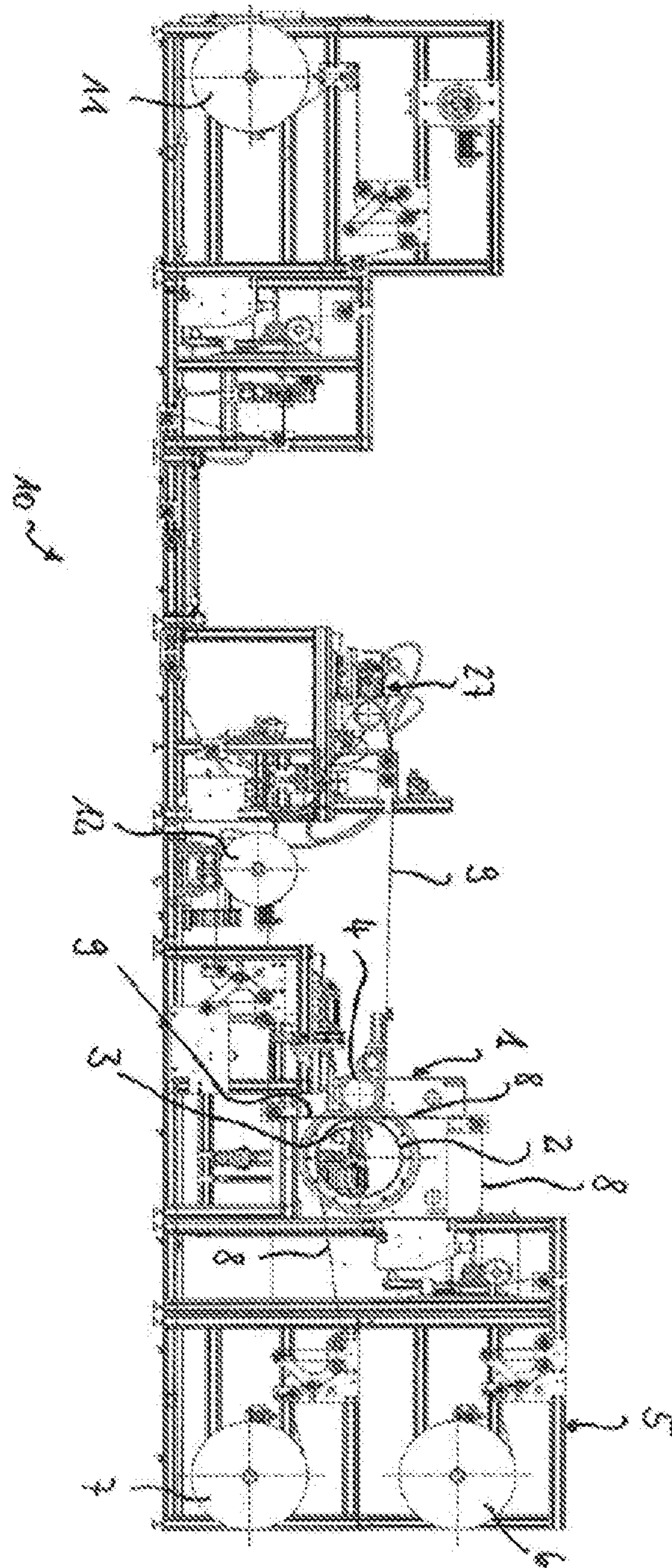


Fig. 2

